



# Advanced Solid-State Devices

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Atlas Simulation  
Assignments

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# Part 1: P-N Junction

Assume that we are designing a long silicon diode with step junction and doping concentrations of  $10^{19} \text{ Atom.cm}^{-3}$  for phosphorous and  $10^{19} \text{ Atom.cm}^{-3}$  for boron

1. Draw electron and hole concentrations (mark depletion regions), electric potential (fermi level), 4 current components (drift and diffusion for both carrier types) and doping concentrations for zero bias, forward bias and reverse bias.

## Defining the structure:

```
go atlas

#Adding the meshings
mesh
x.m l=0.0 spac=1.0
x.m l=1.0 spac=1.0
y.m l=0.0 spac=1.0
y.m l=5.0 spac=0.005
y.m l=15 spac=2.0

region num=1 silicon

#Naming the P-Type Silicon Cathode and N-Type Silicon Anode
electrode top name=cathode
electrode bottom name=cathode

# Doping Concentration
doping uniform p.type conc=1e19 x.l=0 x.r=1 y.t=0.0 y.b=5.0
doping uniform n.type conc=1e19 x.l=0 x.r=1 y.t=5.0 y.b=15.0
```

. Higher mesh density around the junction



## Adding the Physical and Numerical models:

```
#Physical Models
models srh conmob bgn auger fldmob

#Impact Ionization model
impact selb

#Adding newton numerical model
method newton climit=1.e-5

#Solving the P-N junction in equilibrium
solve init

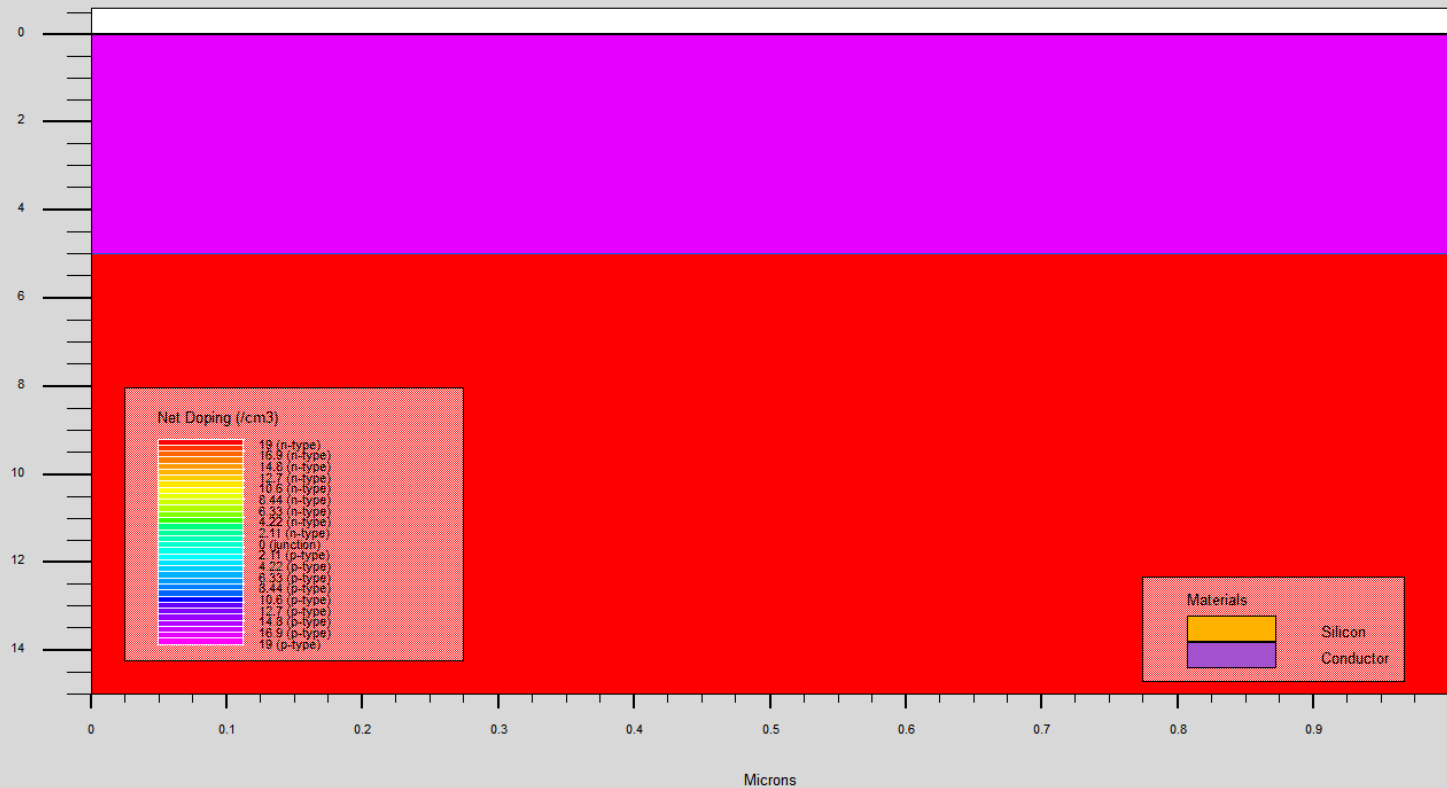
#Getting all the Carrier Concentrations and Energy bands and diagrams
output band.temp

save outf=pn2.str
tonyplot pn2.str
```

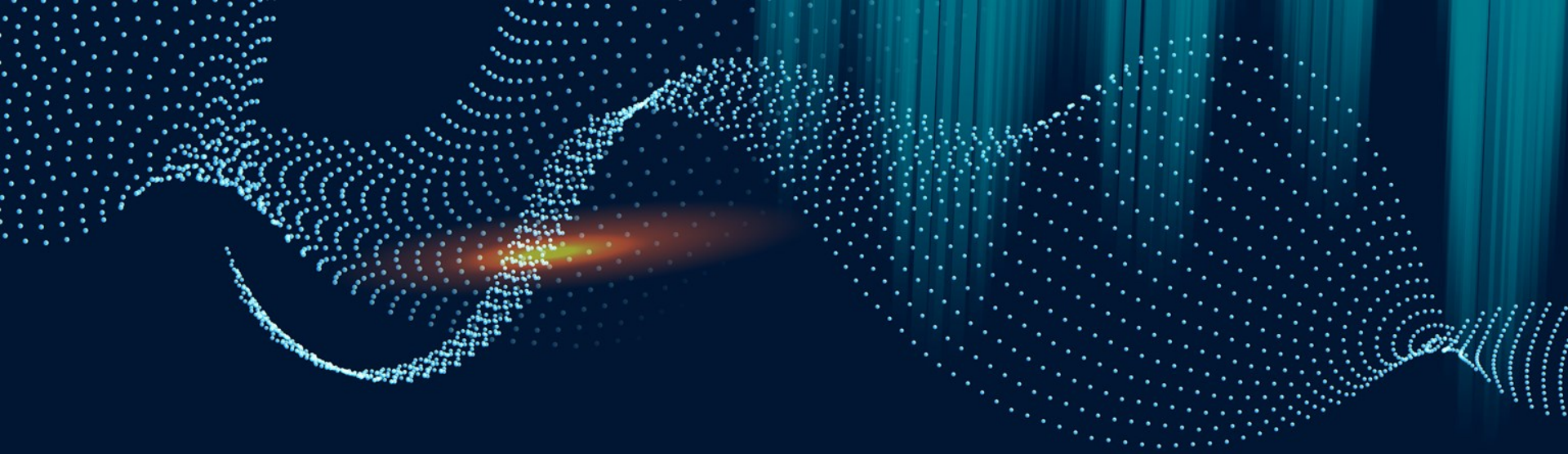
**srh:** Shockley-Read-Hall recombination model.  
**conmob:** Concentration-dependent mobility model.  
**bgn:** Bandgap narrowing model.  
**auger:** Auger recombination model.  
**fldmob:** Field-dependent mobility model.

ATLAS

Data from pn2.str



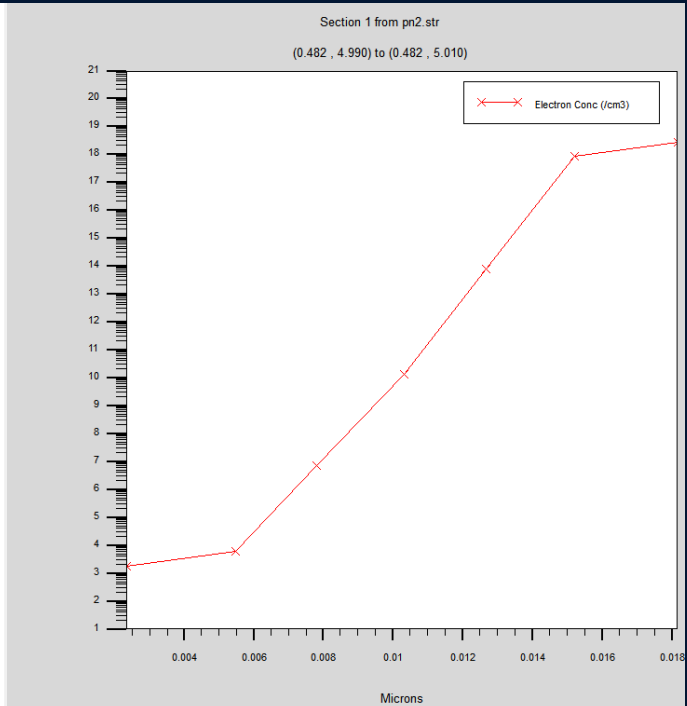
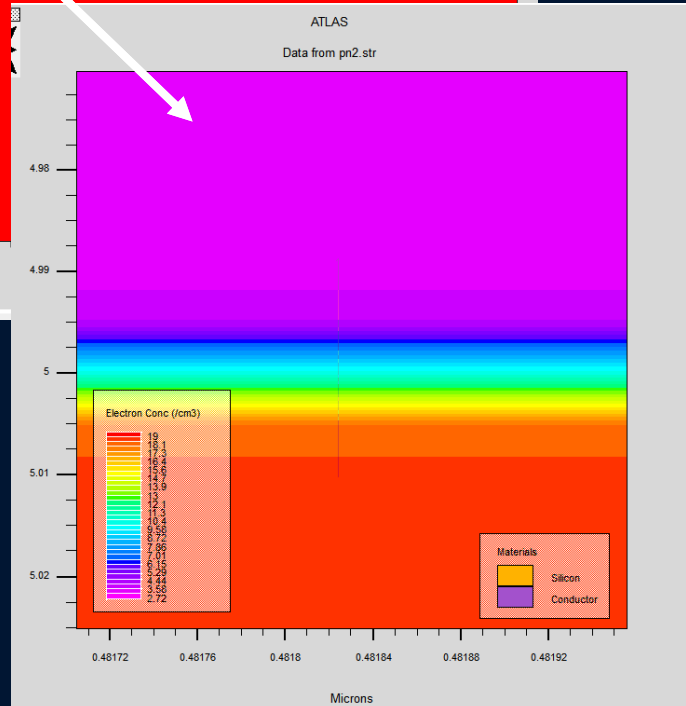
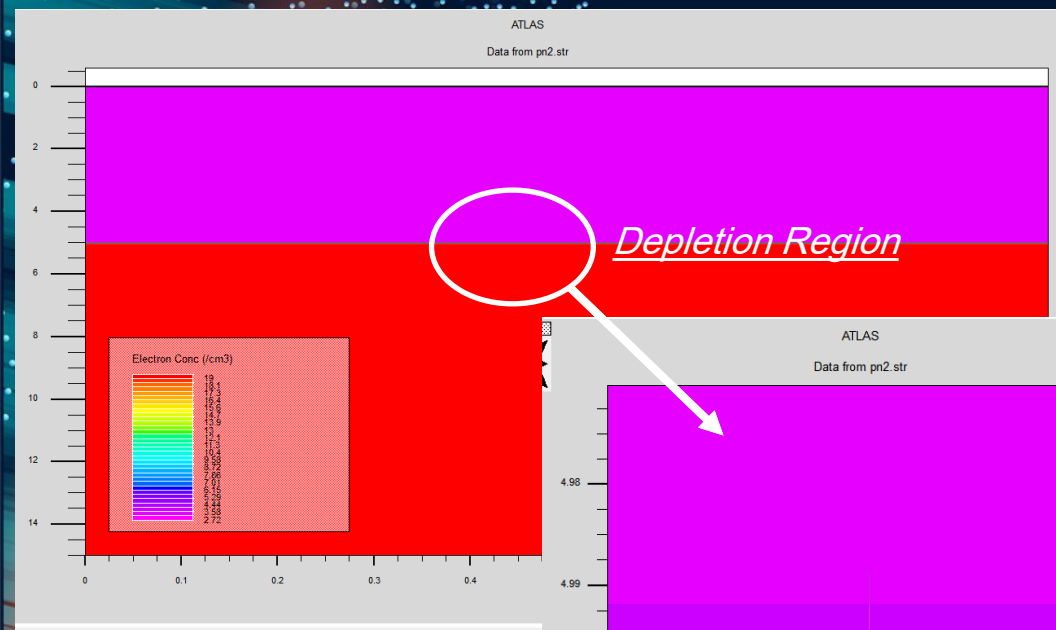




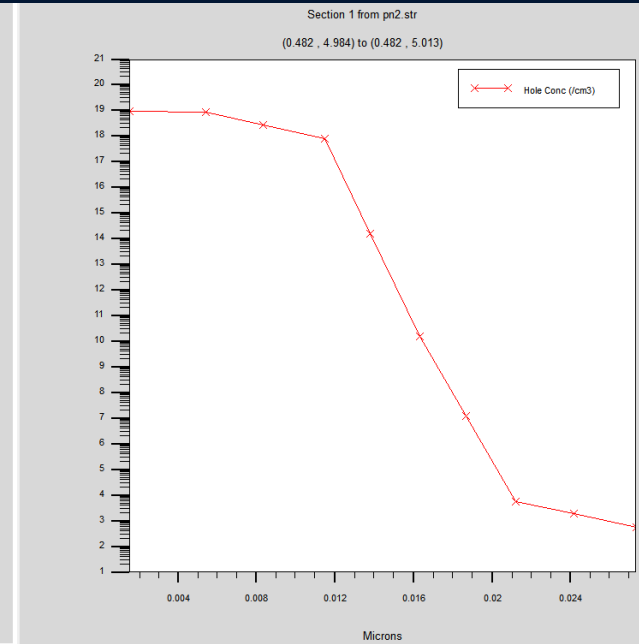
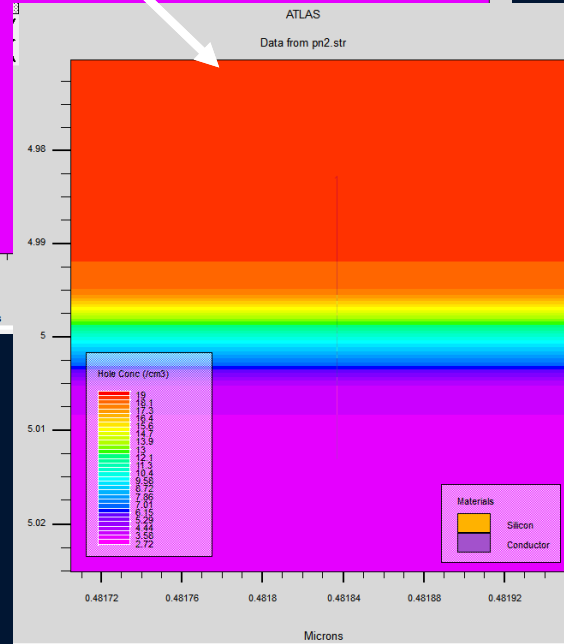
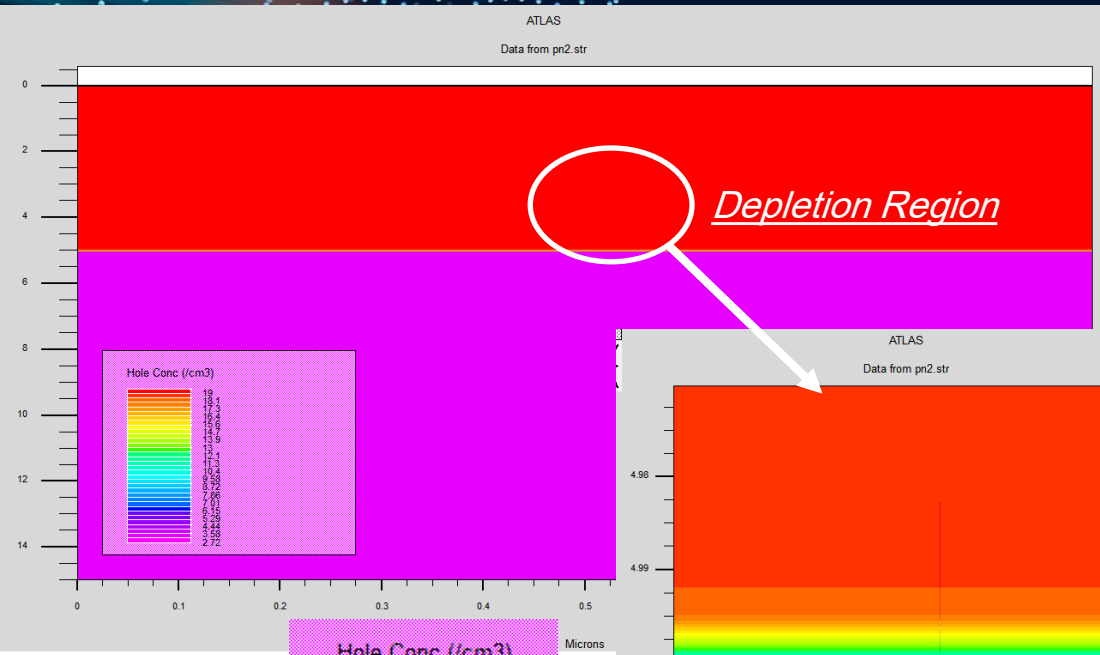
**01**

**Zero Bias**

# Zero Bias: Electron Concentrations

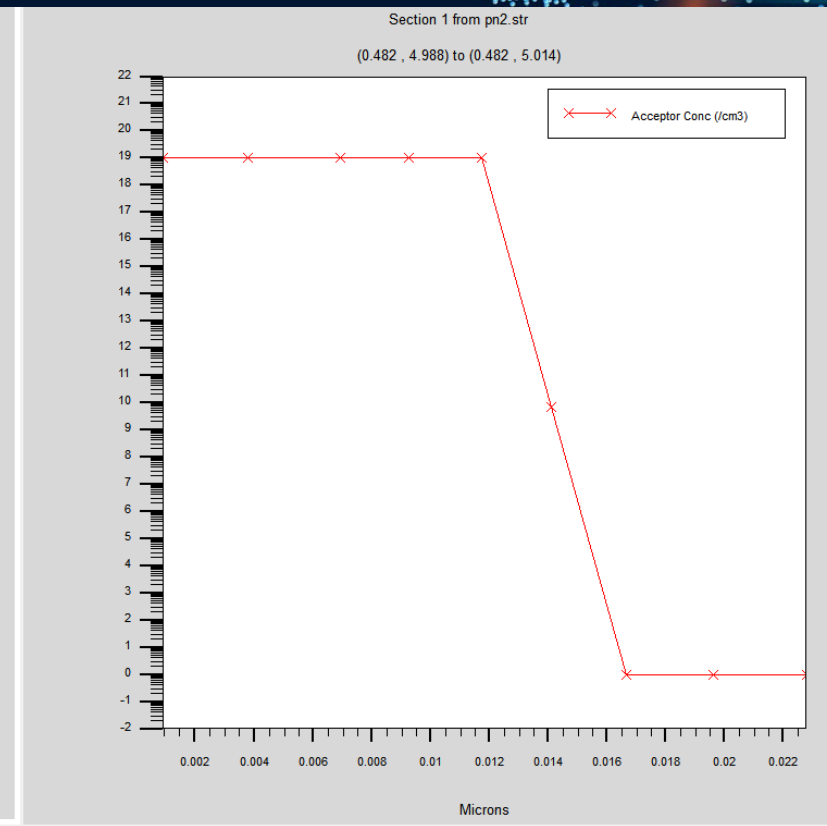
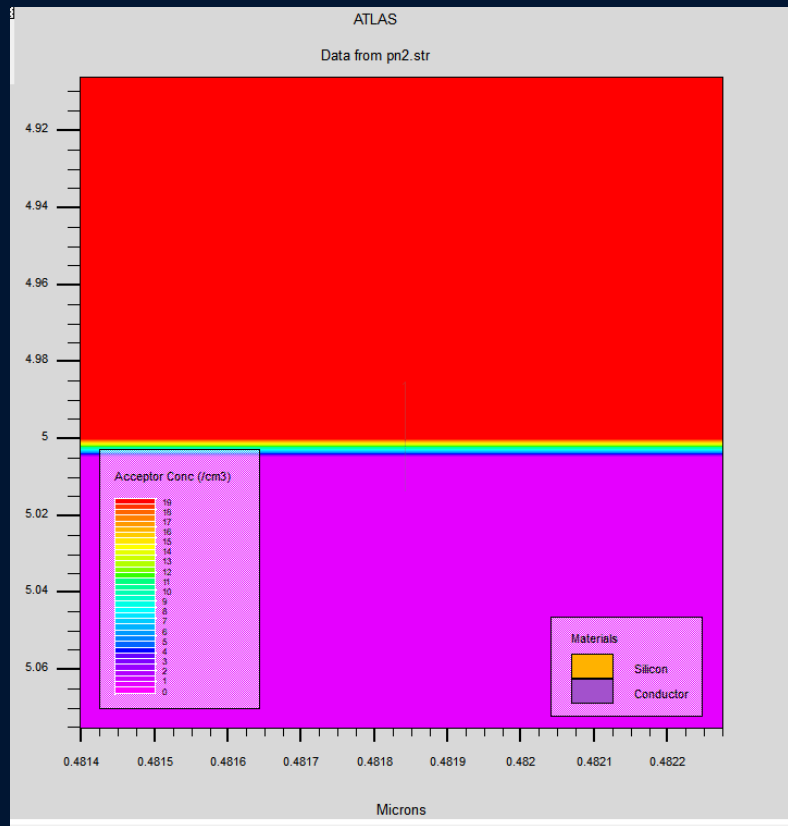


# Zero Bias: Hole Concentrations

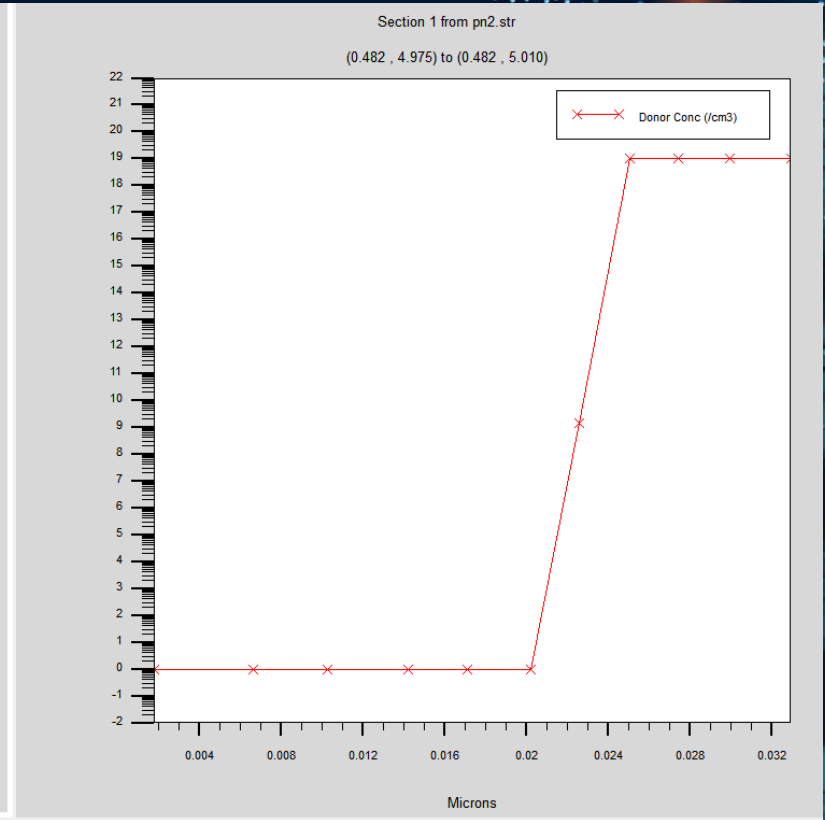
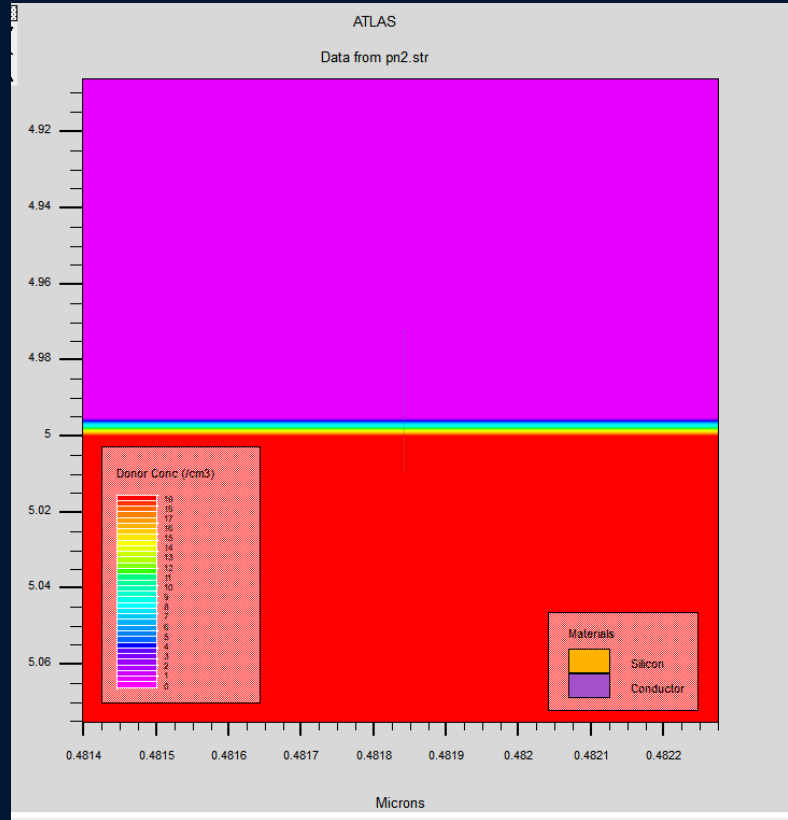




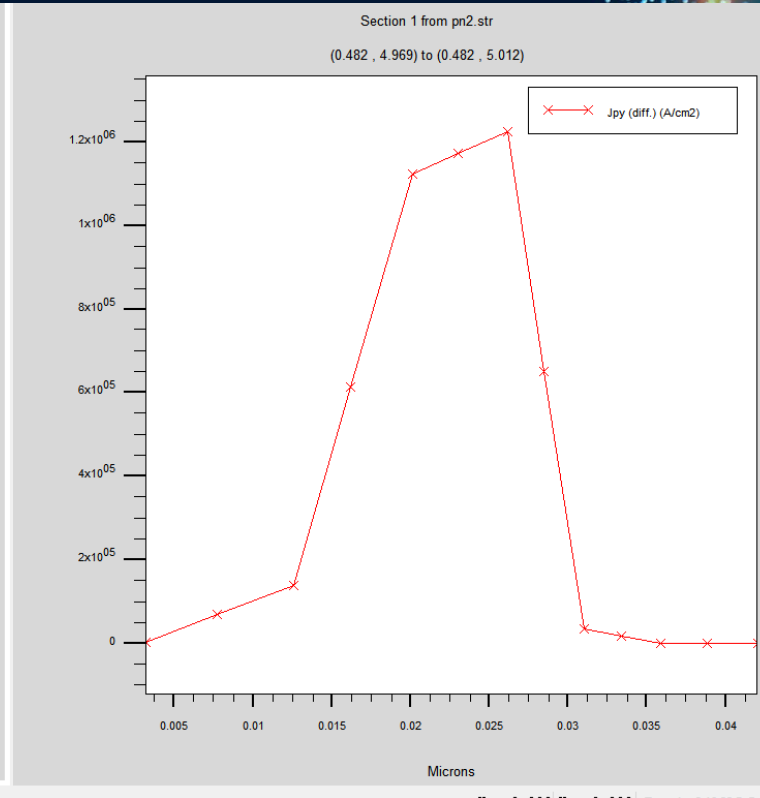
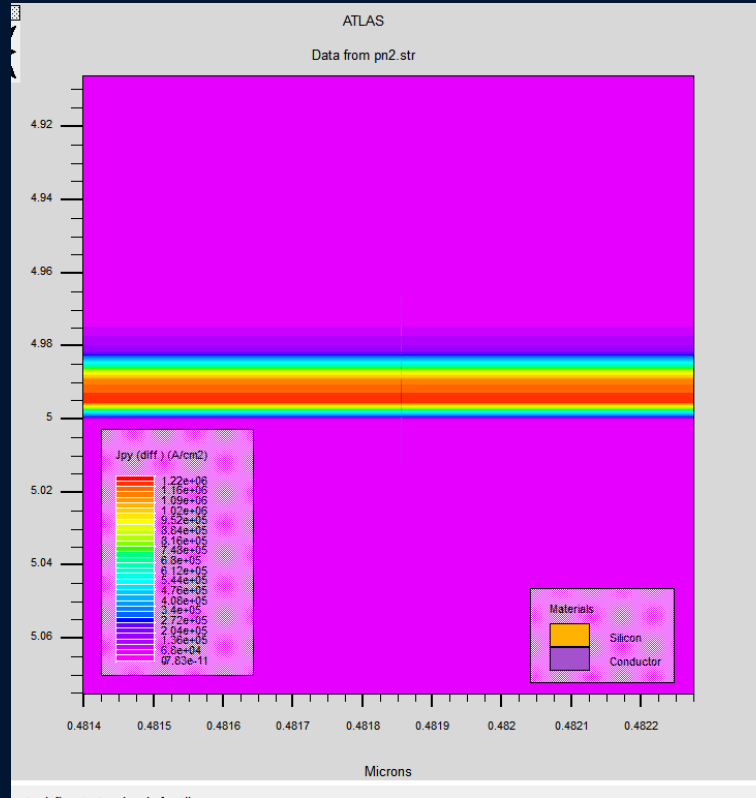
# Zero Bias: Acceptor Concentrations



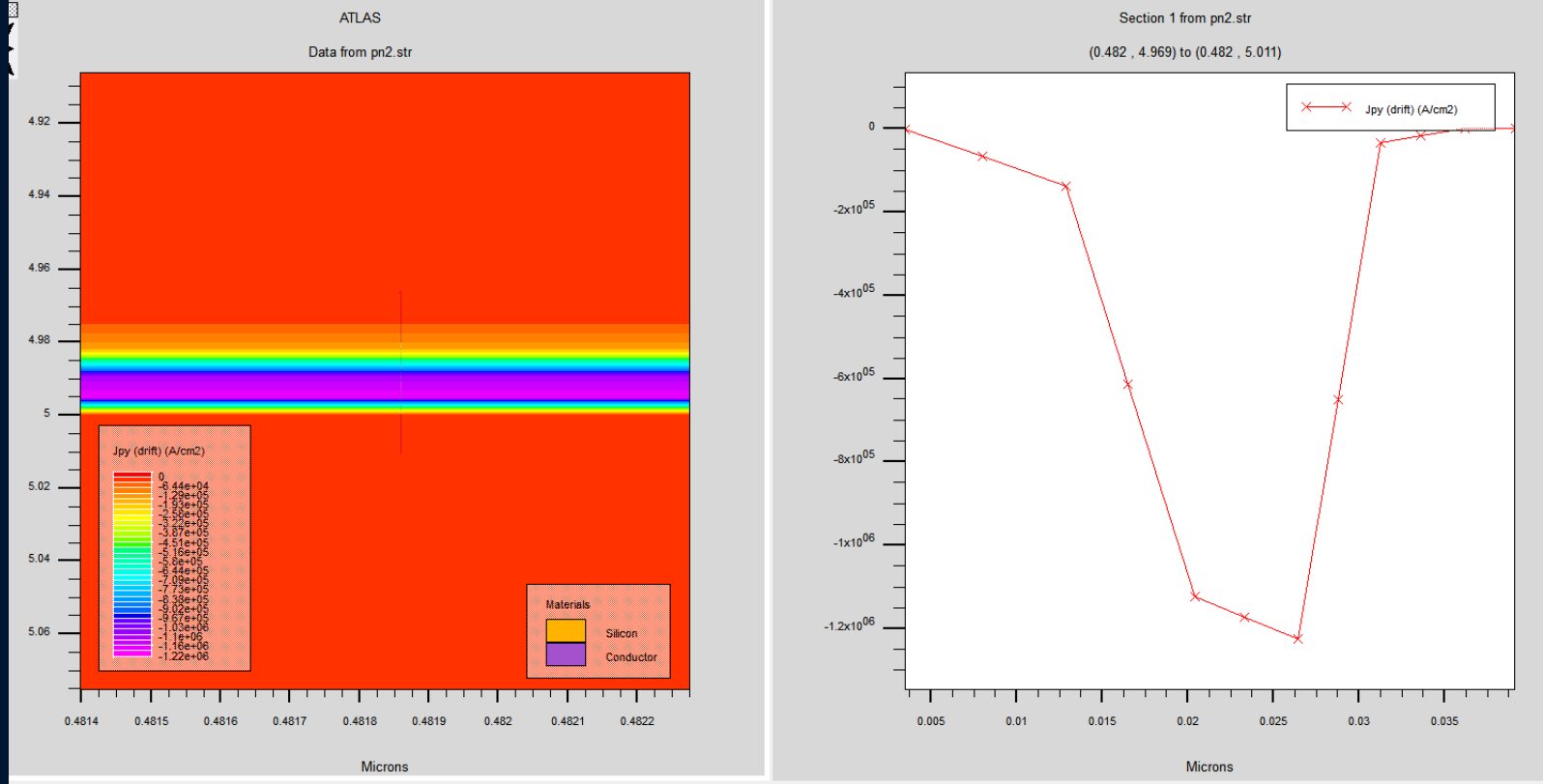
# Zero Bias: Donor Concentrations



# Zero Bias: $J_{py}$ (Holes Diffusion Current)

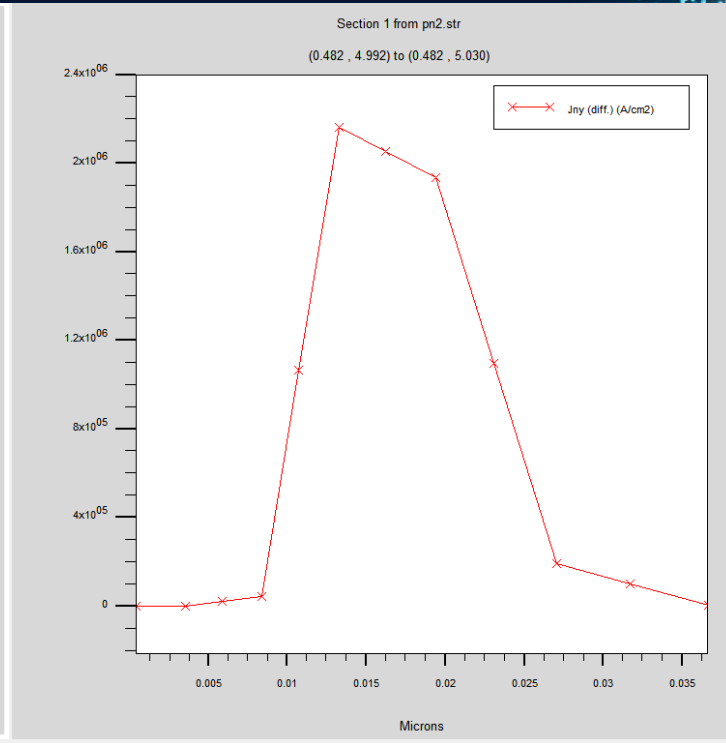
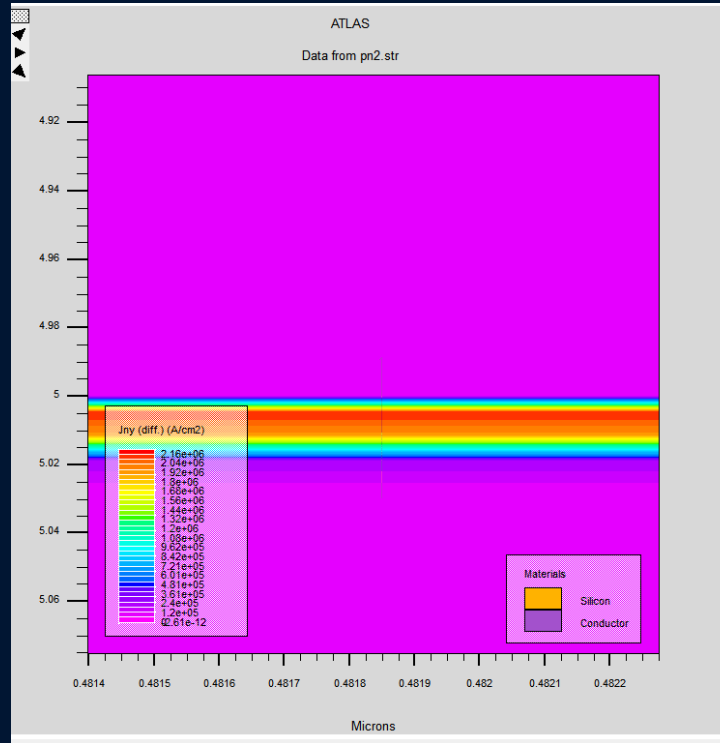


# Zero Bias: Jpy (Holes Drift Current)

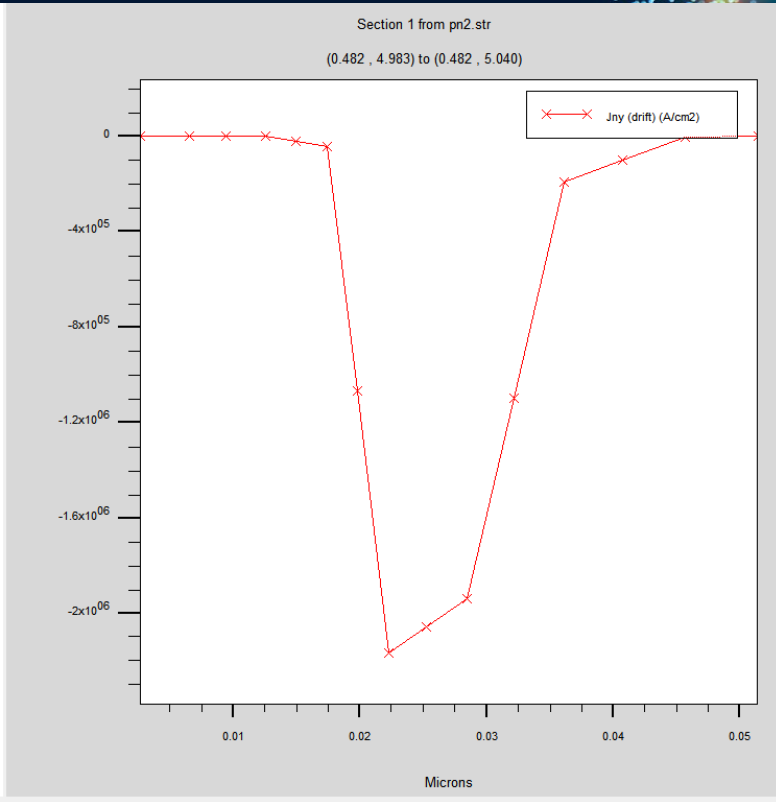
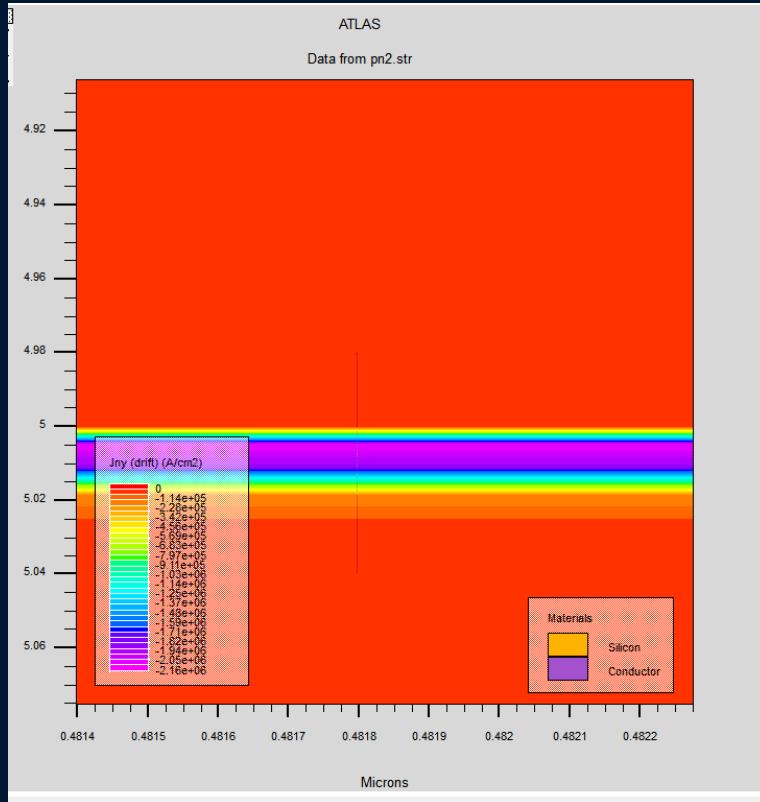


As we expected, the total hole current (Drift + Diffusion) under equilibrium is equal to zero.

# Zero Bias: $J_{ny}$ (Electrons Diffusion Current)

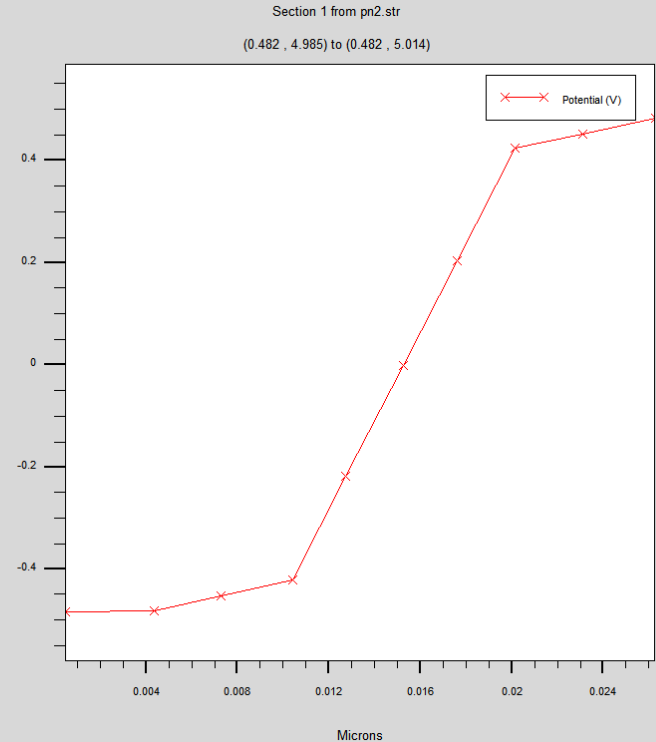
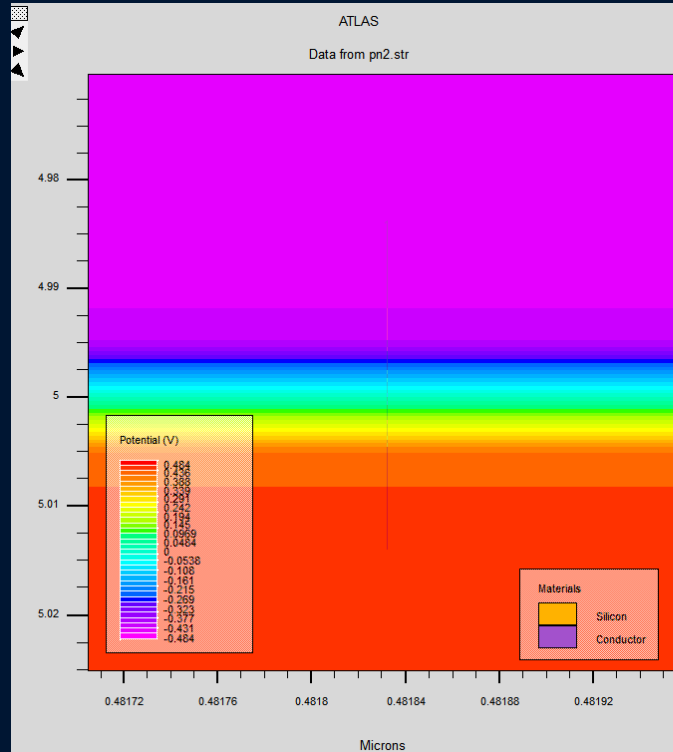


# Zero Bias: $J_{ny}$ (Electrons Drift Current)

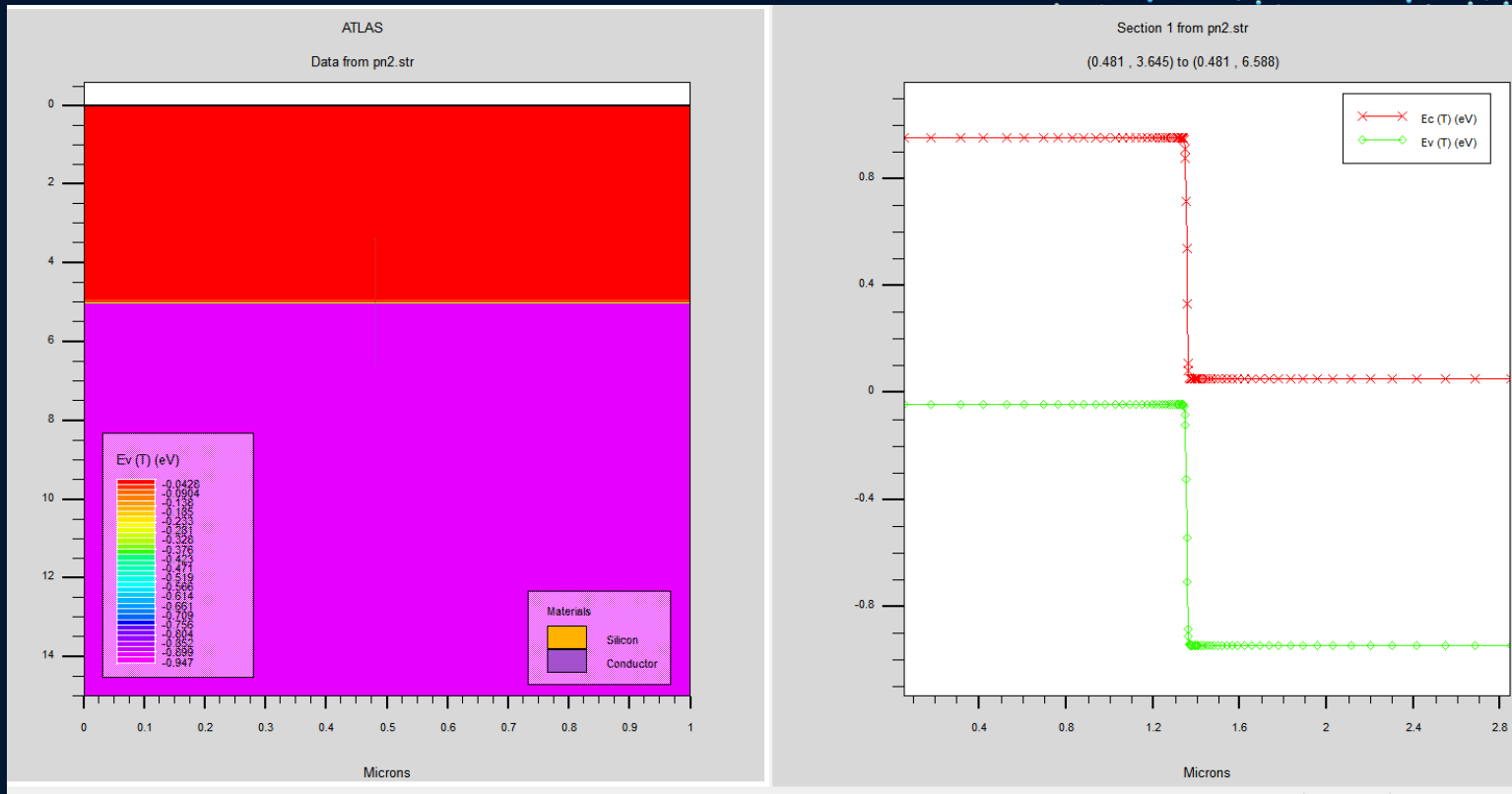


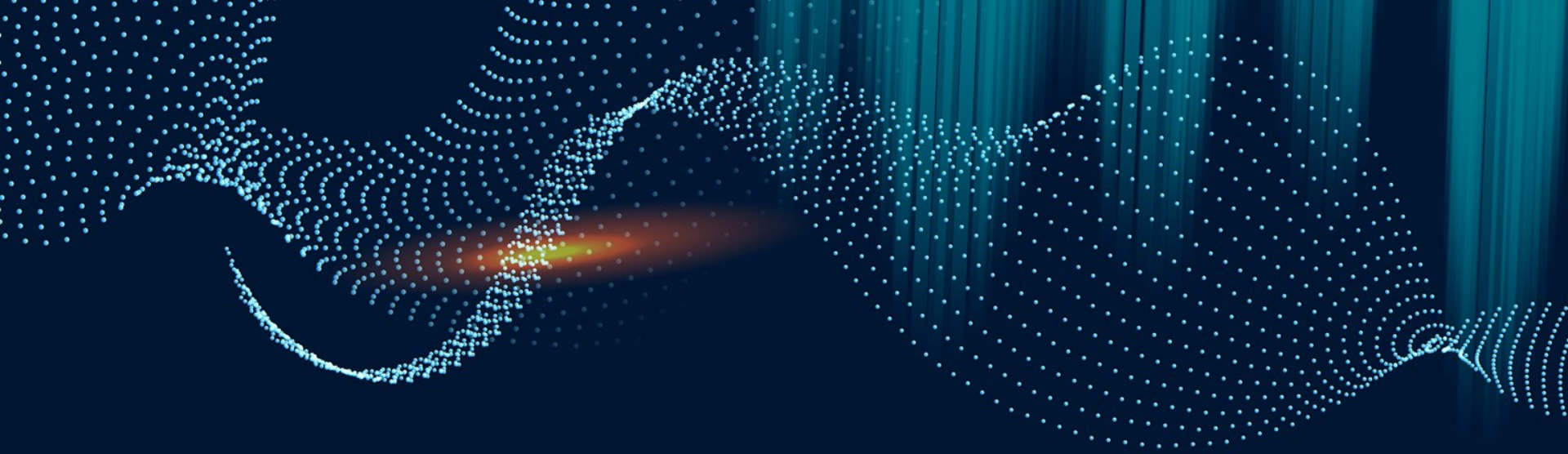


# Zero Bias: Electric Potential



# Zero Bias: Energy Band Diagrams

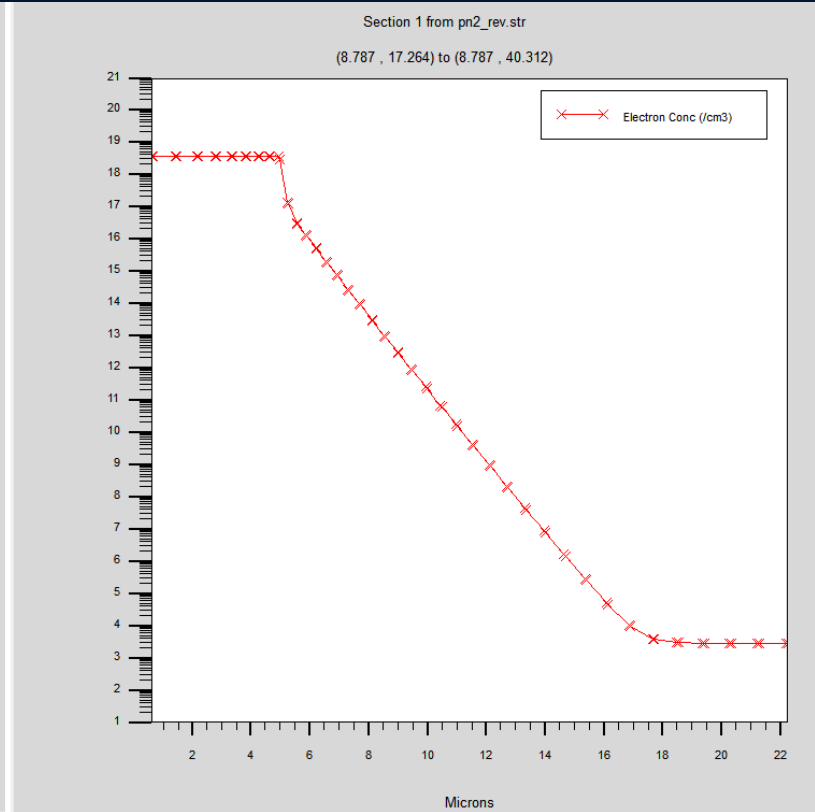
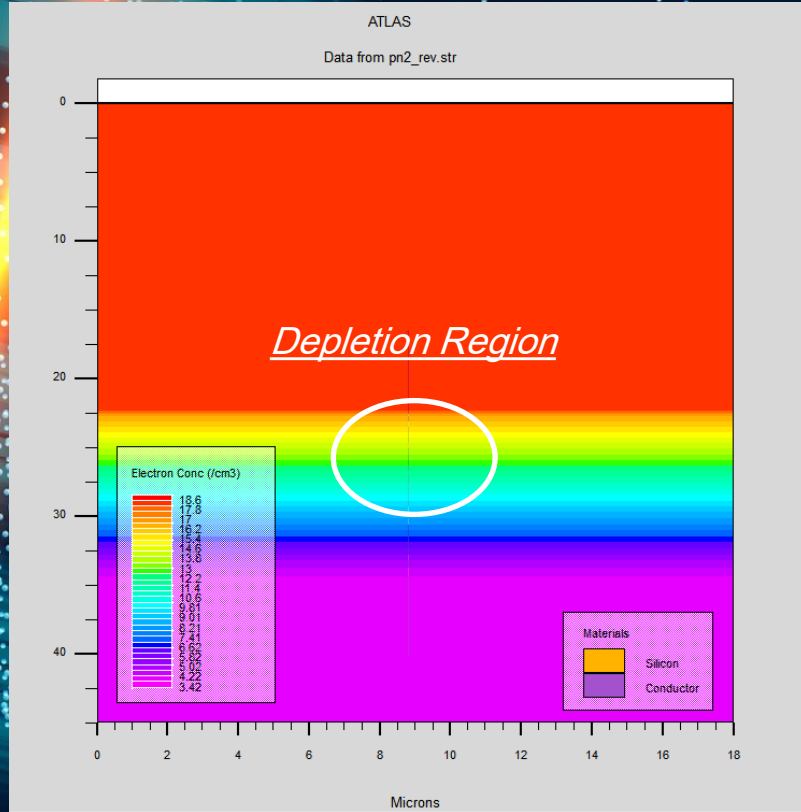




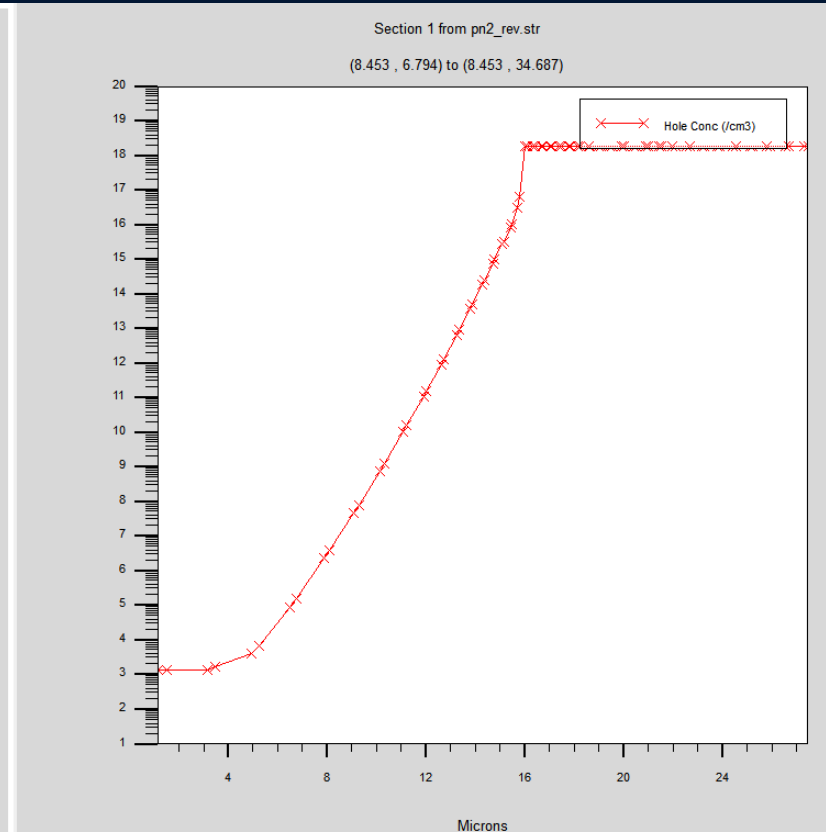
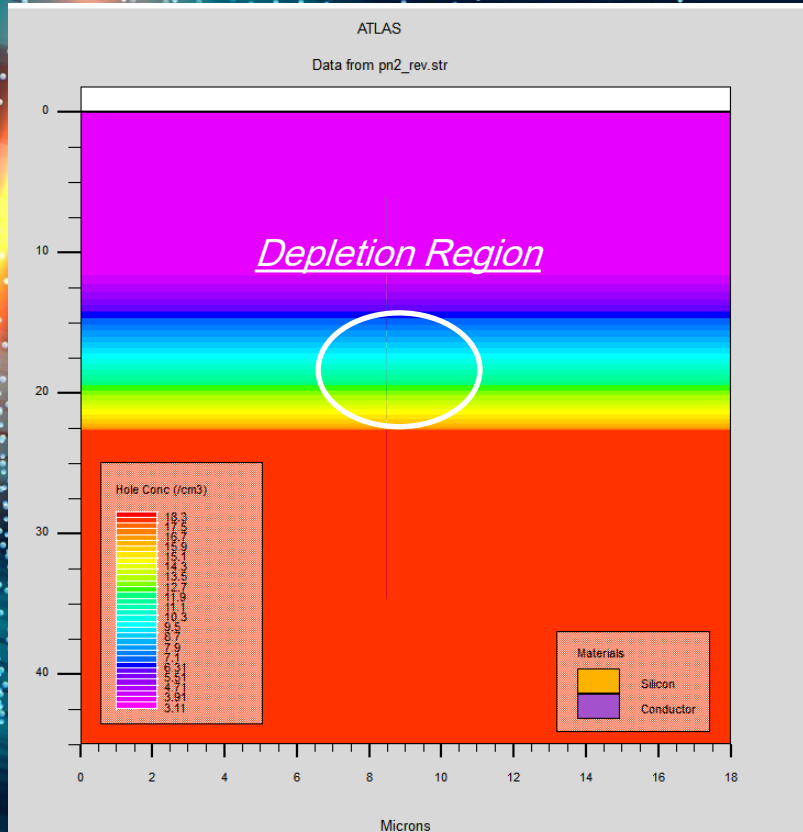
**02**

**Reverse Bias**

# Reverse Bias: Electron Concentrations



## Reverse Bias: Hole Concentrations



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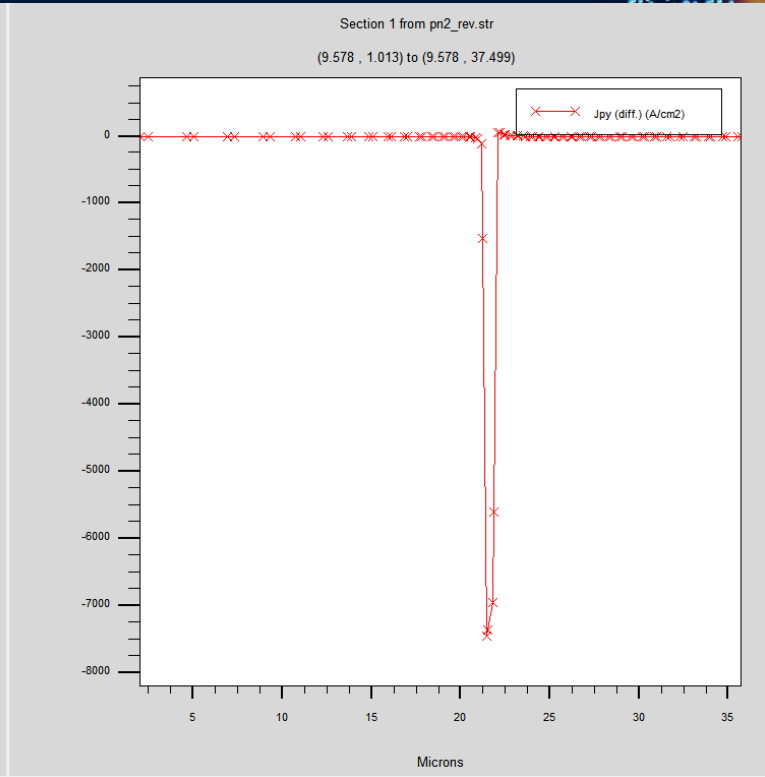
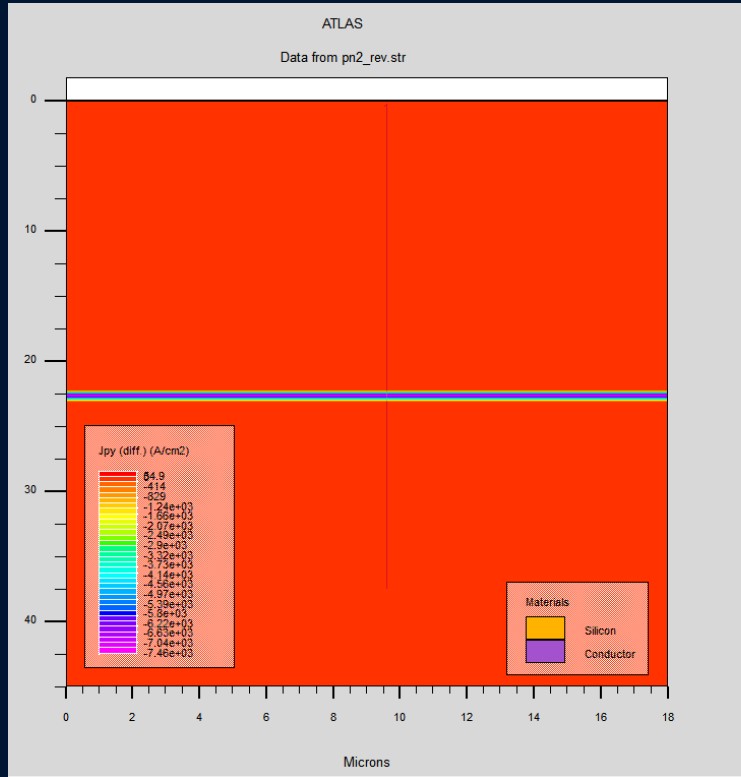
# Forward and Reverse Bias: Donor and Acceptor Concentrations

The donor and acceptor concentrations are just the same as the zero bias case on the 8<sup>th</sup> and 9<sup>th</sup> slides!

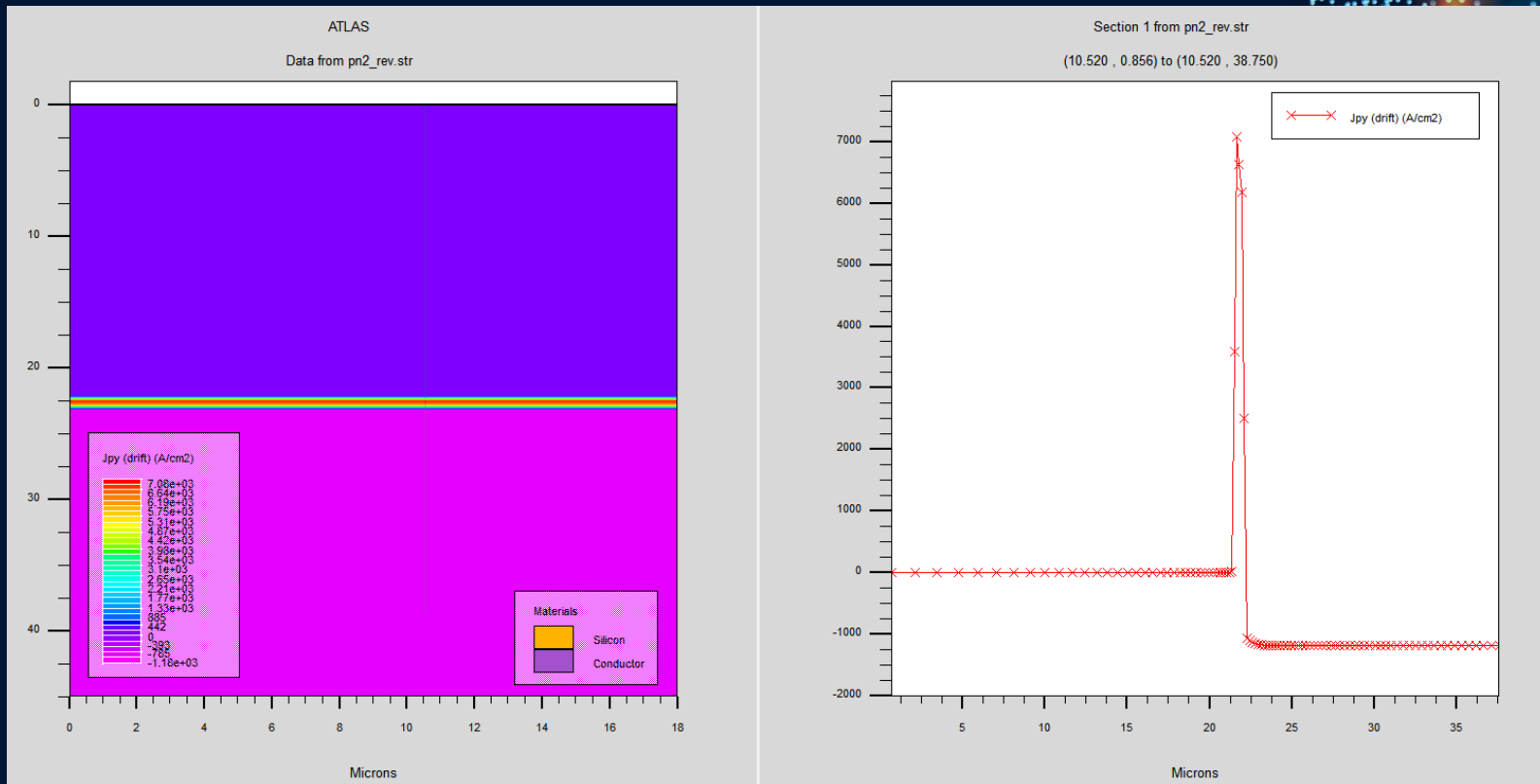




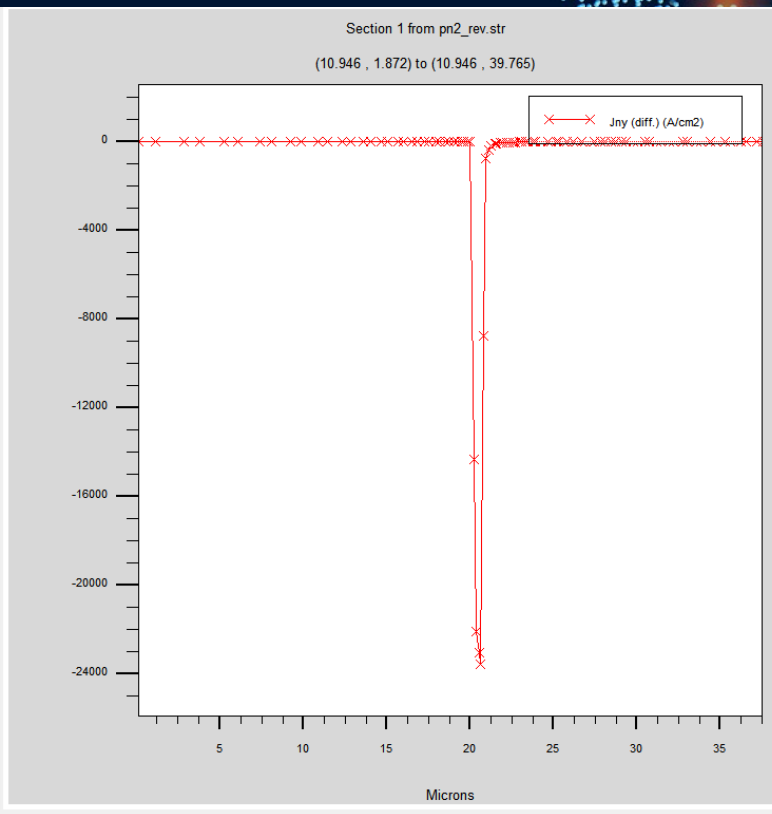
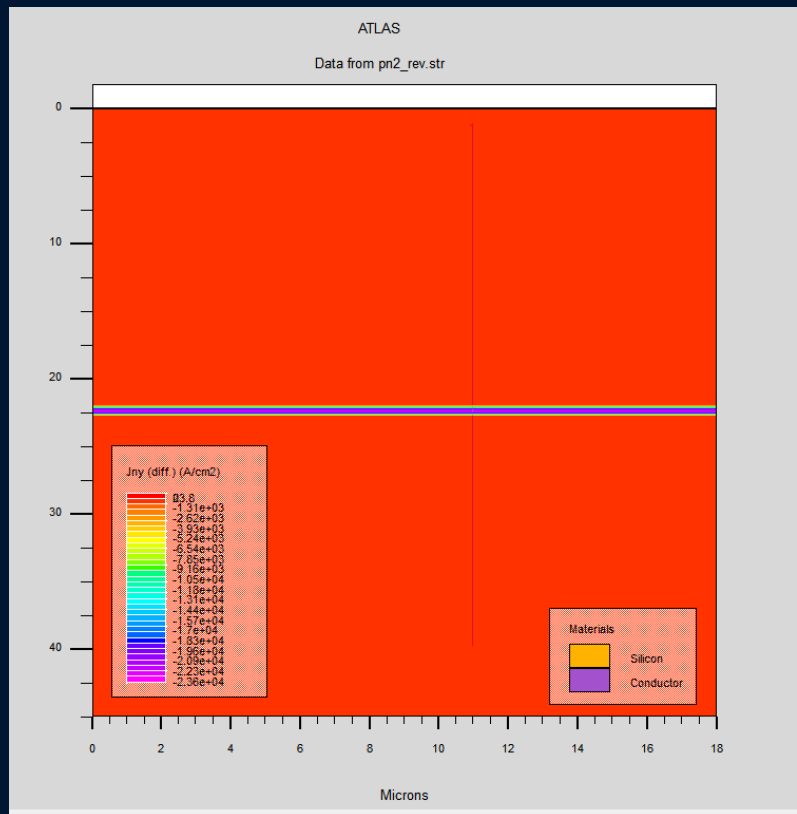
# Reverse Bias: $J_{py}$ (Holes Diffusion Current)



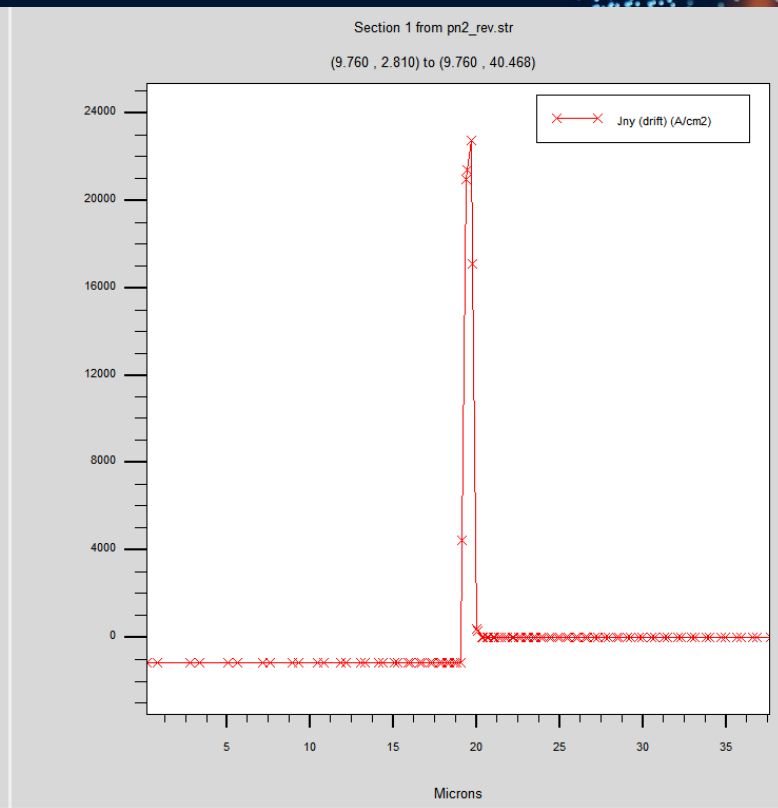
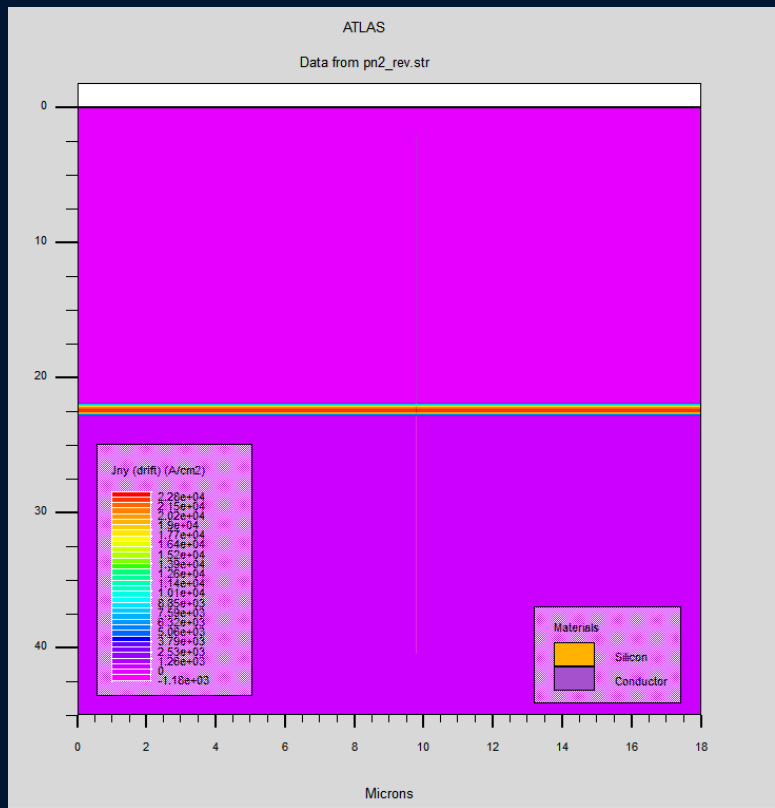
# Reverse Bias: $J_{py}$ (Holes Drift Current)



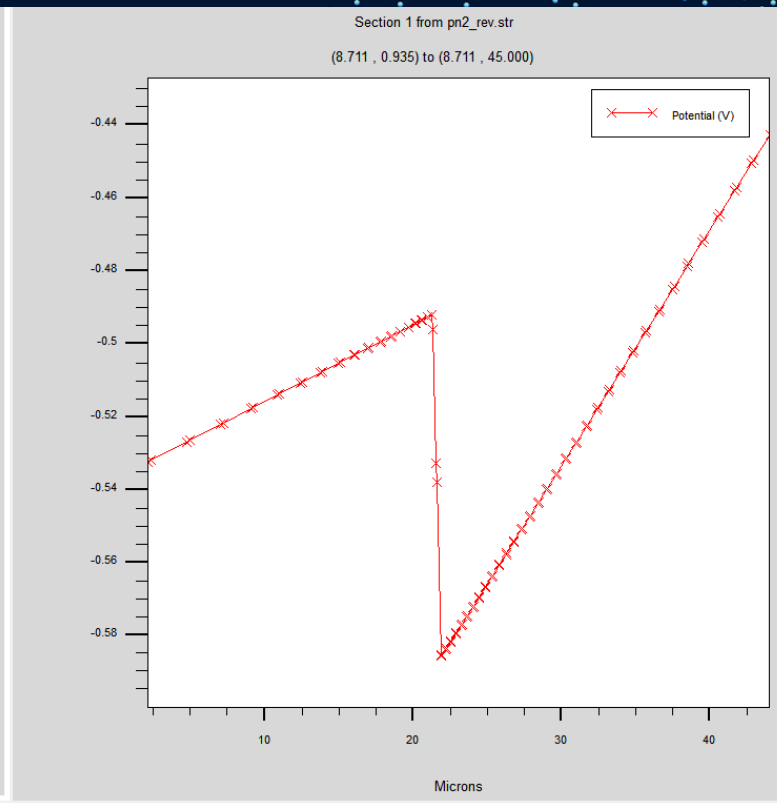
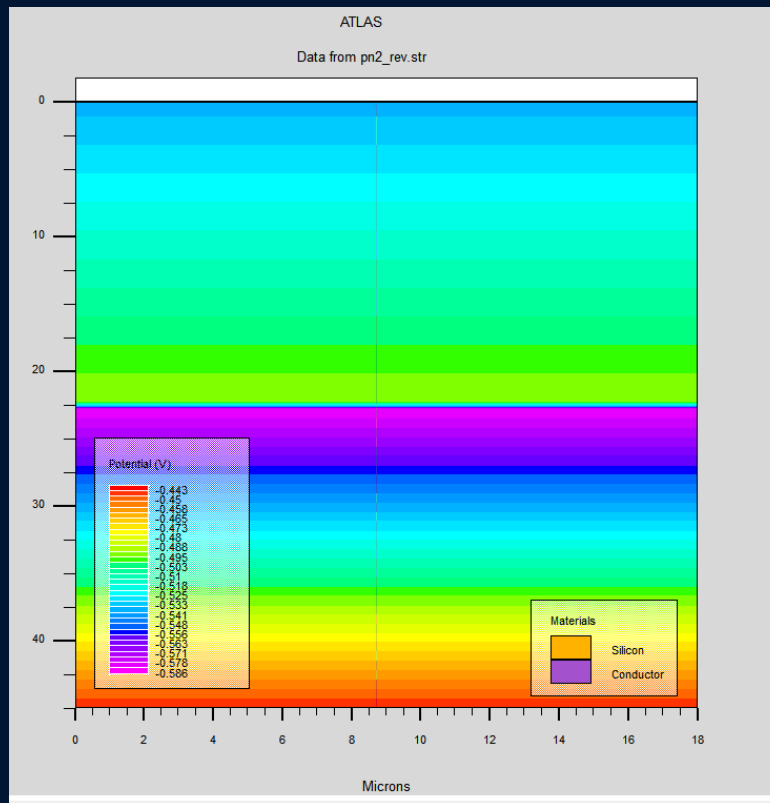
# Reverse Bias: $J_{ny}$ (Electrons Diffusion Current)



# Reverse Bias: $J_{ny}$ (Electrons Drift Current)



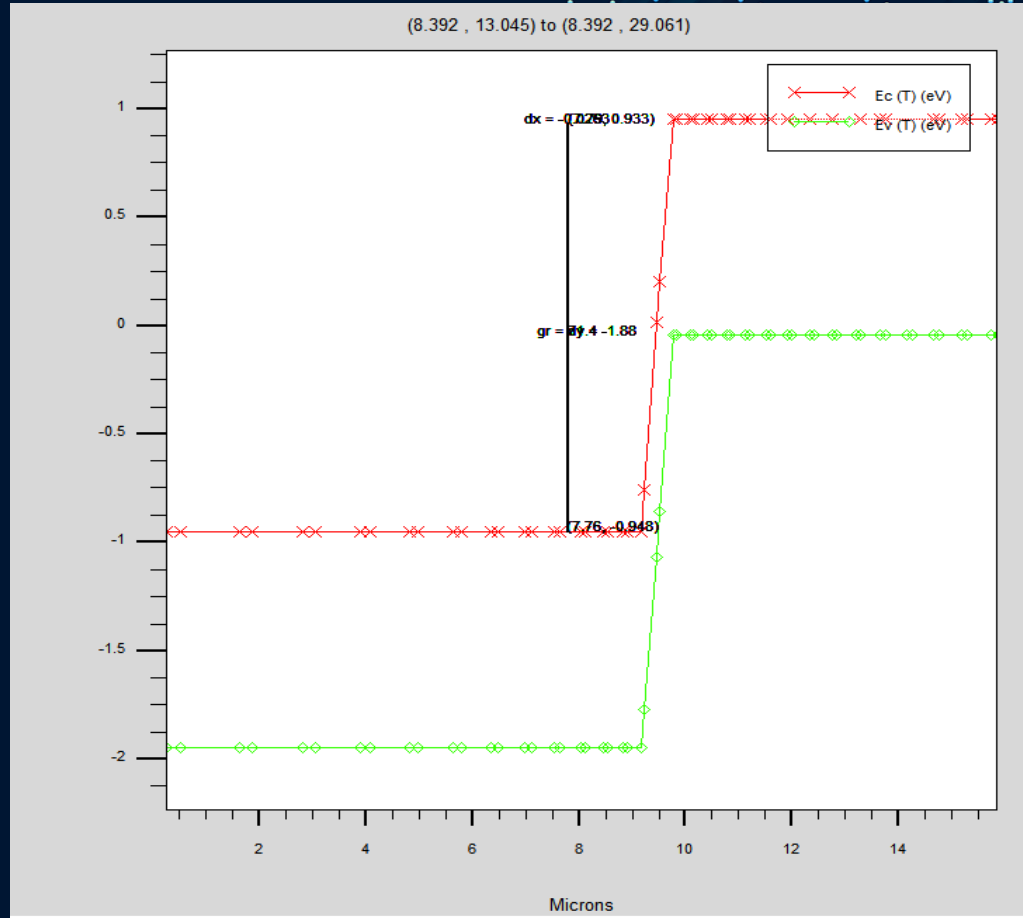
# Reverse Bias: Electric Potential



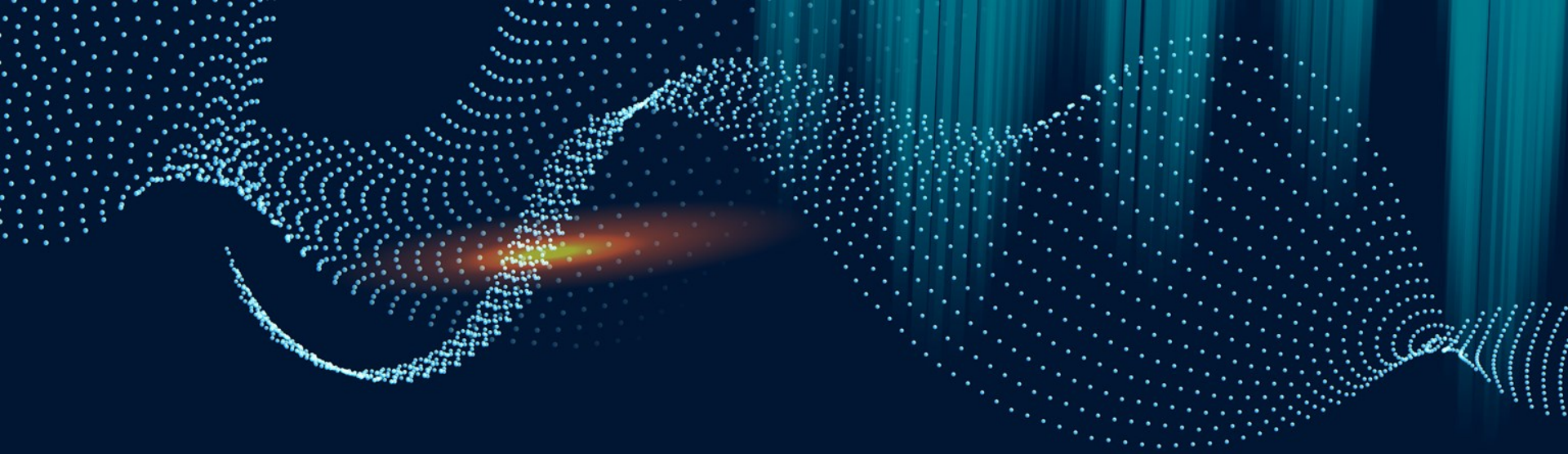
# -1 V Reverse Bias : Energy Band Diagrams

As we can see we have a 1 V shift  
In energy band diagrams due to the  
applied voltage.

$$\rightarrow E_{c,p} - E_{c,n} = e(V_{bi} - V_a)$$



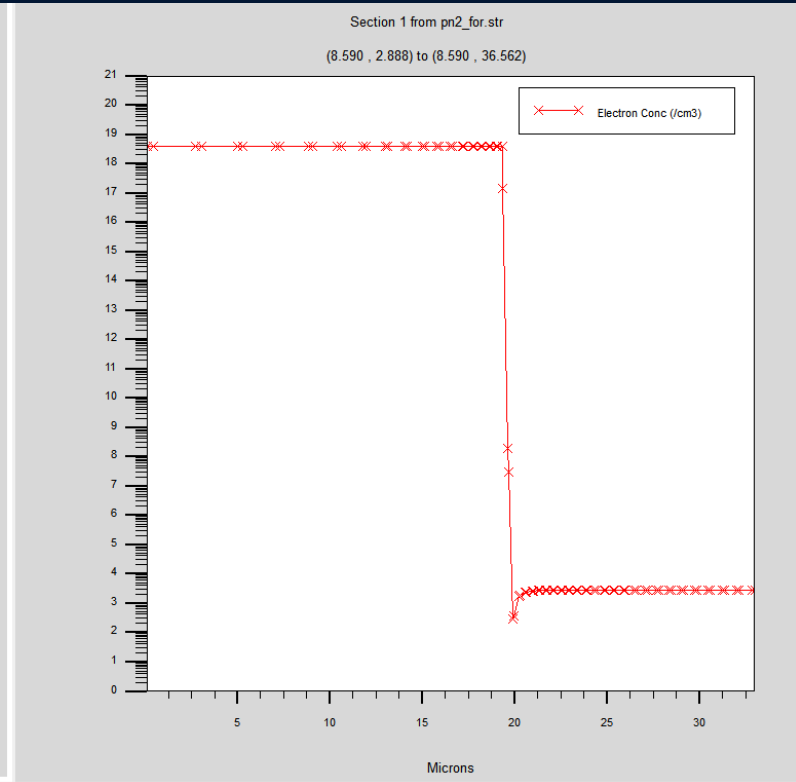
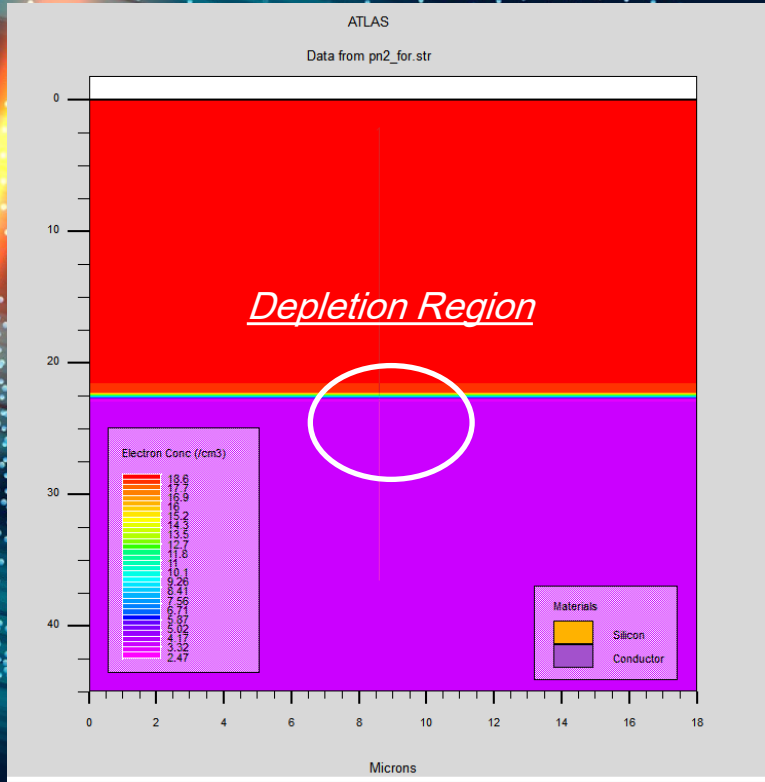




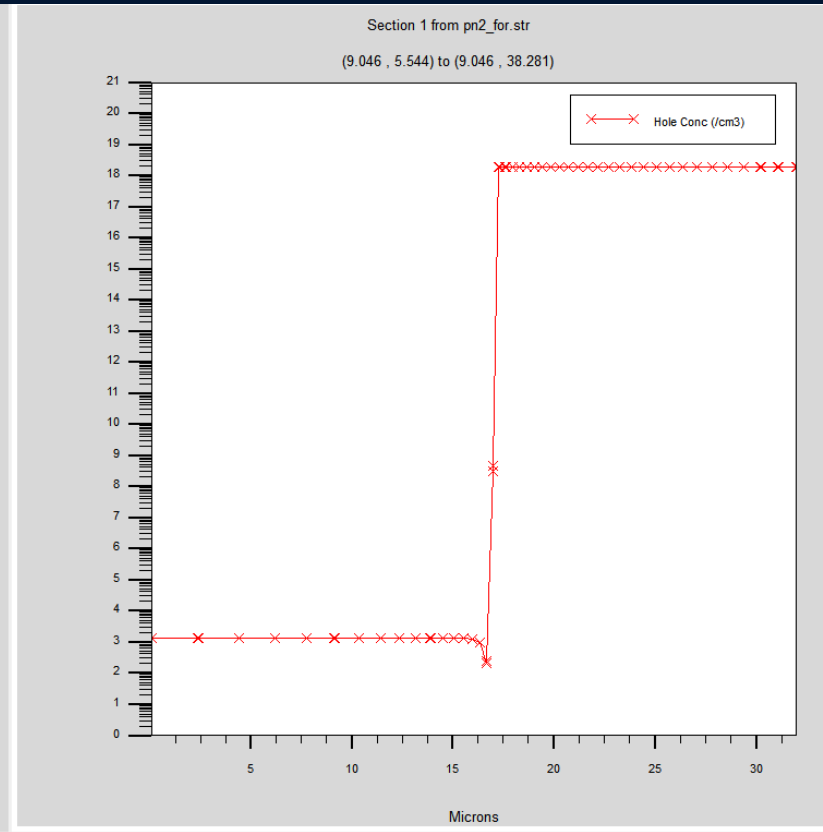
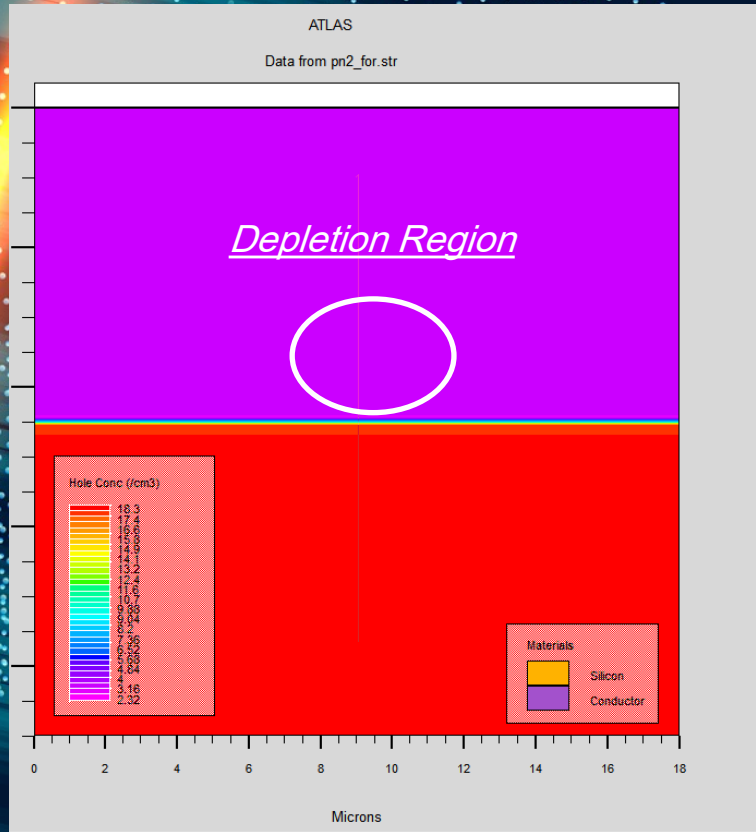
**03**

**Forward Bias**

# Forward Bias: Electron Concentrations



# Reverse Bias: Hole Concentrations



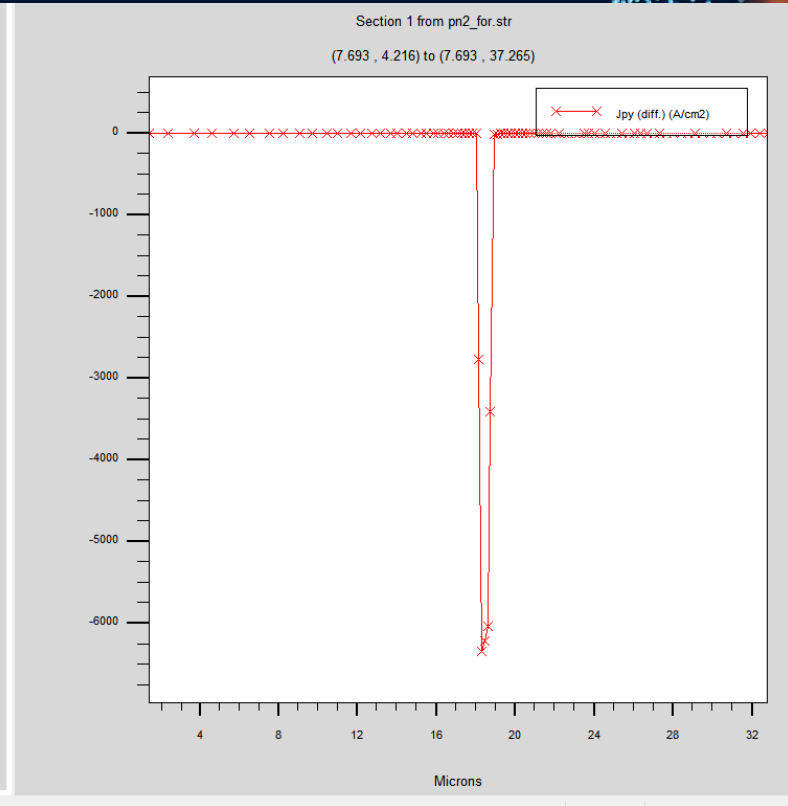
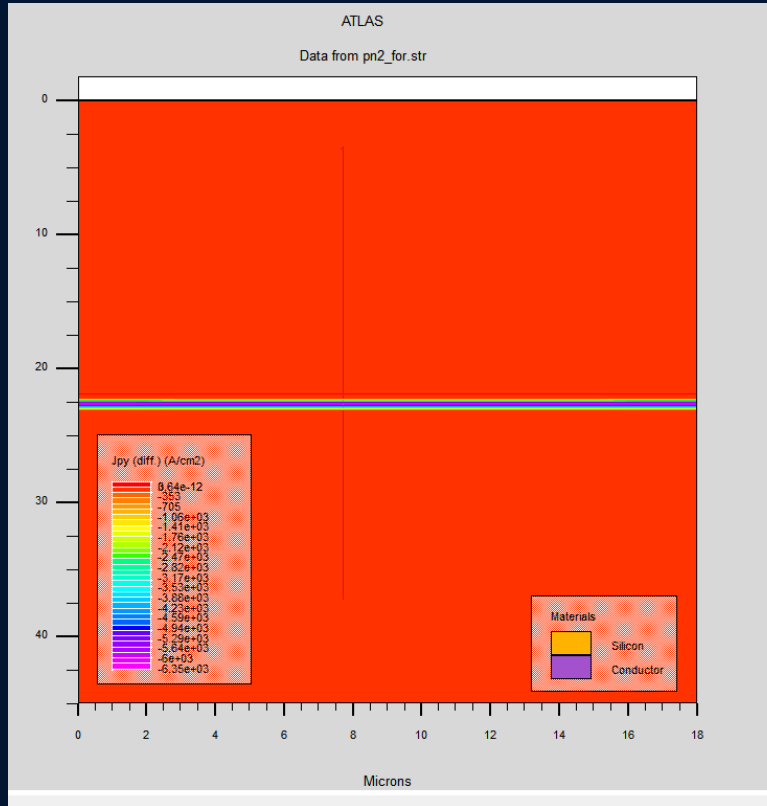
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# Forward and Reverse Bias: Donor and Acceptor Concentrations

The donor and acceptor concentrations are just the same as the zero bias case on the 8<sup>th</sup> and 9<sup>th</sup> slides!



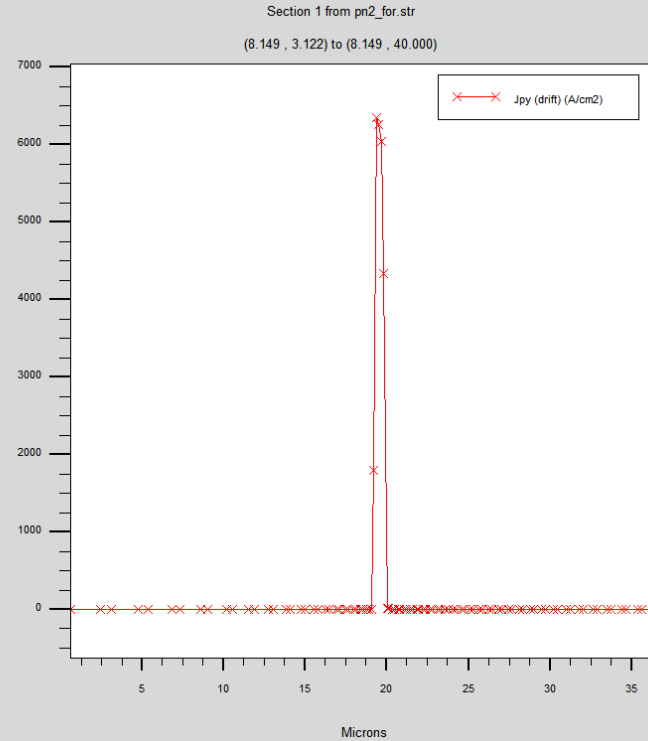
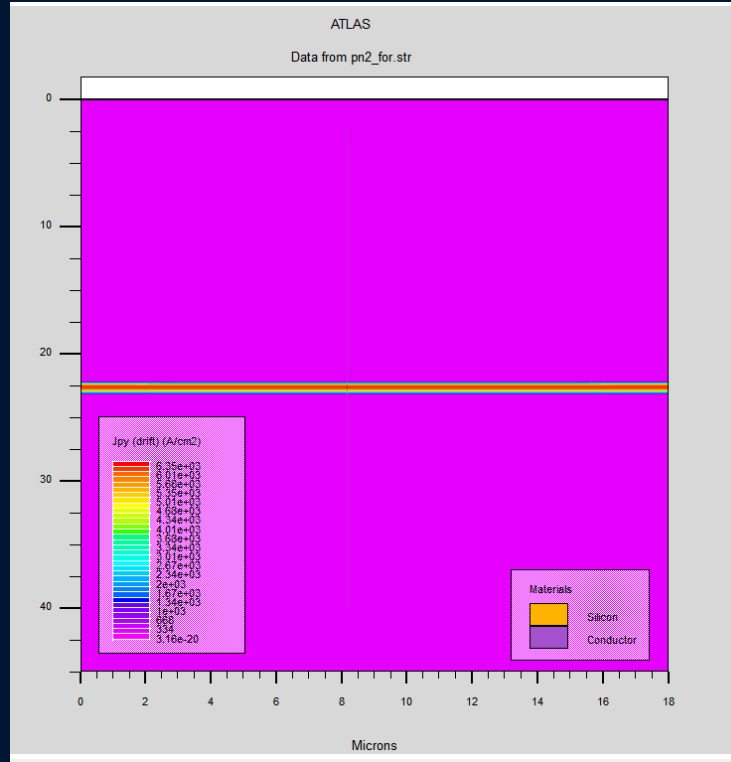
# Forward Bias: $J_{py}$ (Holes Diffusion Current)



The x component of the current is negligible!



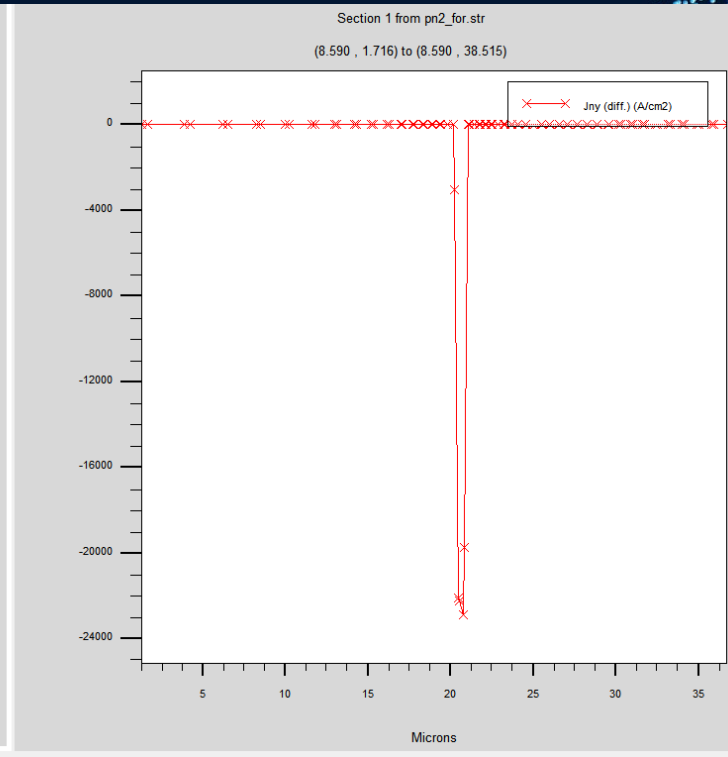
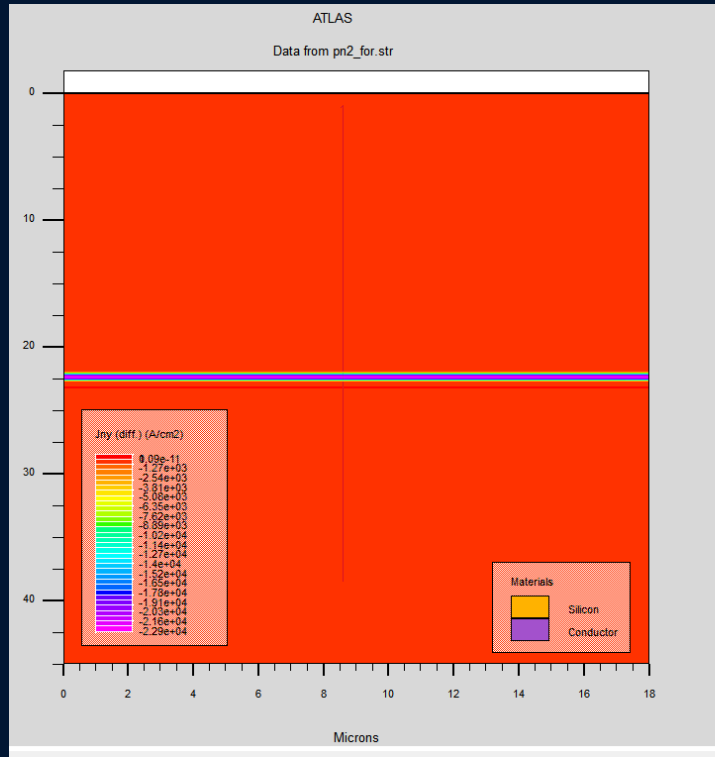
# Forward Bias: $J_{py}$ (Holes Drift Current)



The x component of the current is negligible!

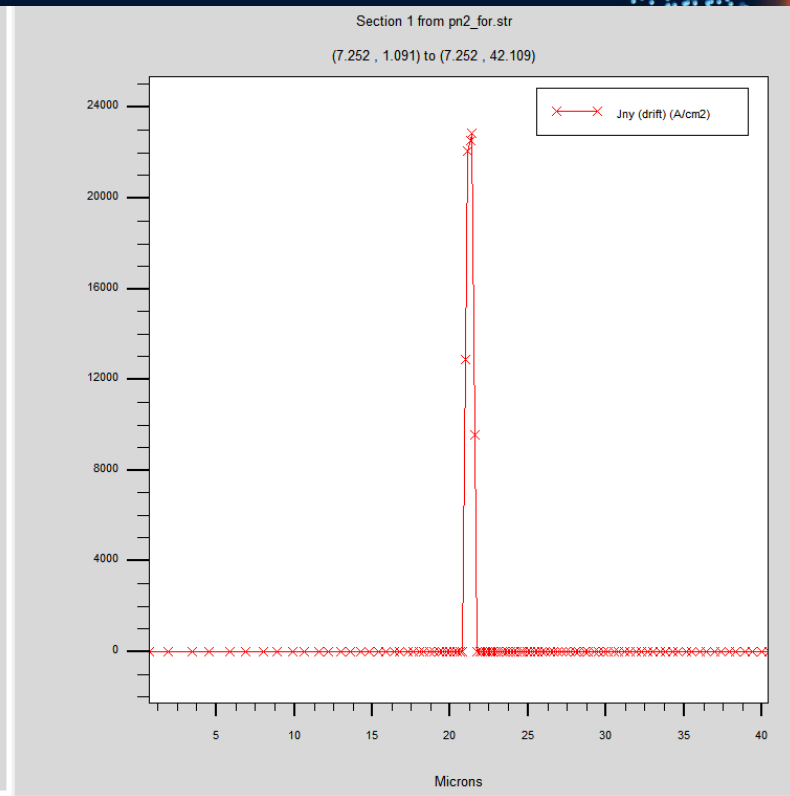
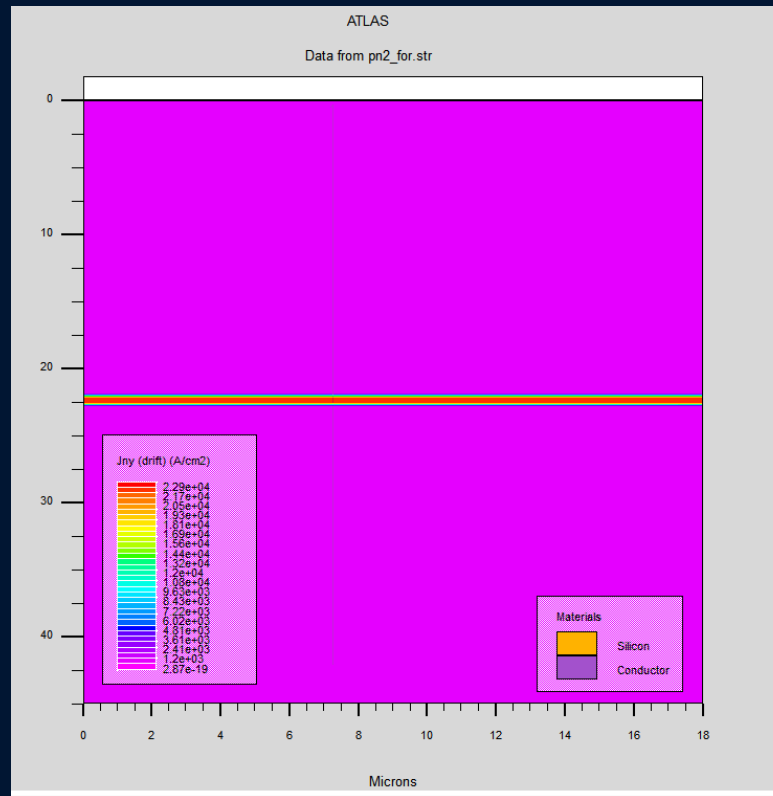


# Forward Bias: $J_{ny}$ (Electrons Diffusion Current)



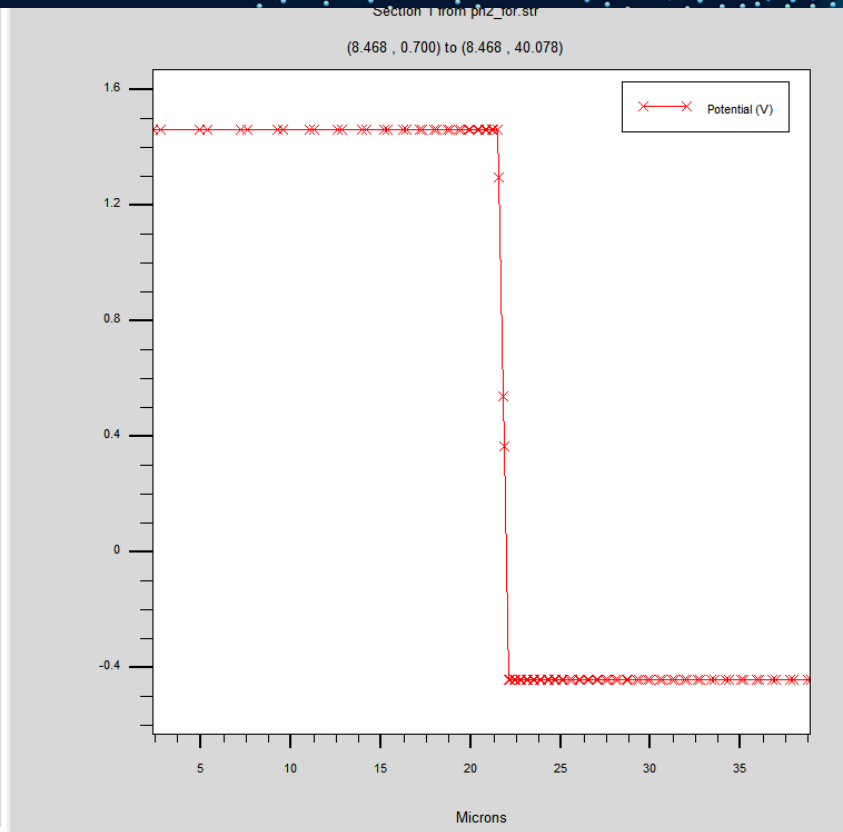
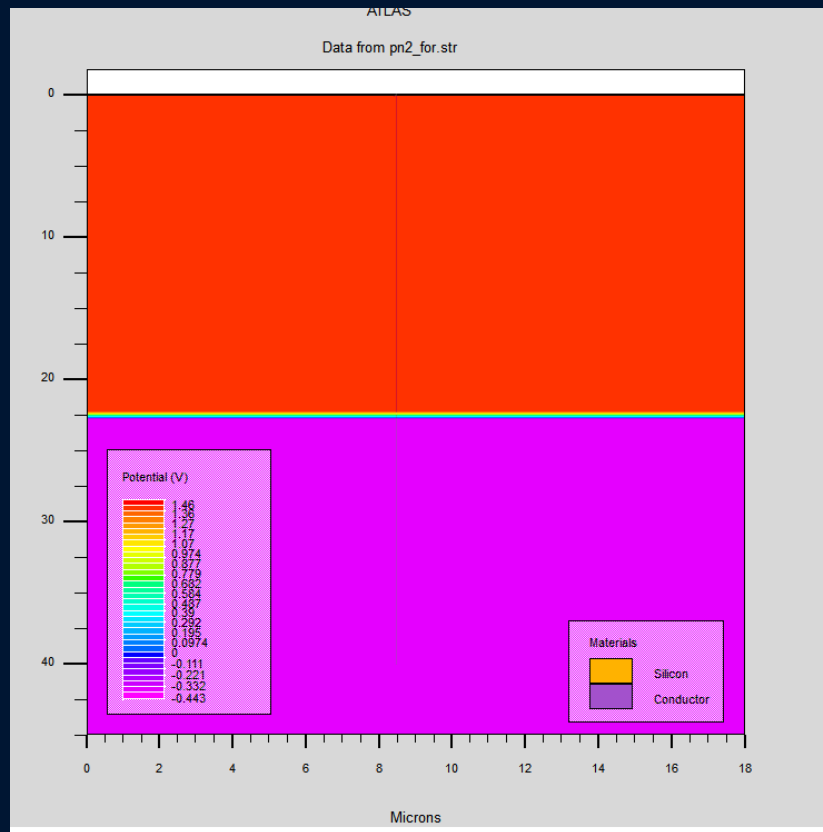
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# Forward Bias: $J_{ny}$ (Electrons Drift Current)



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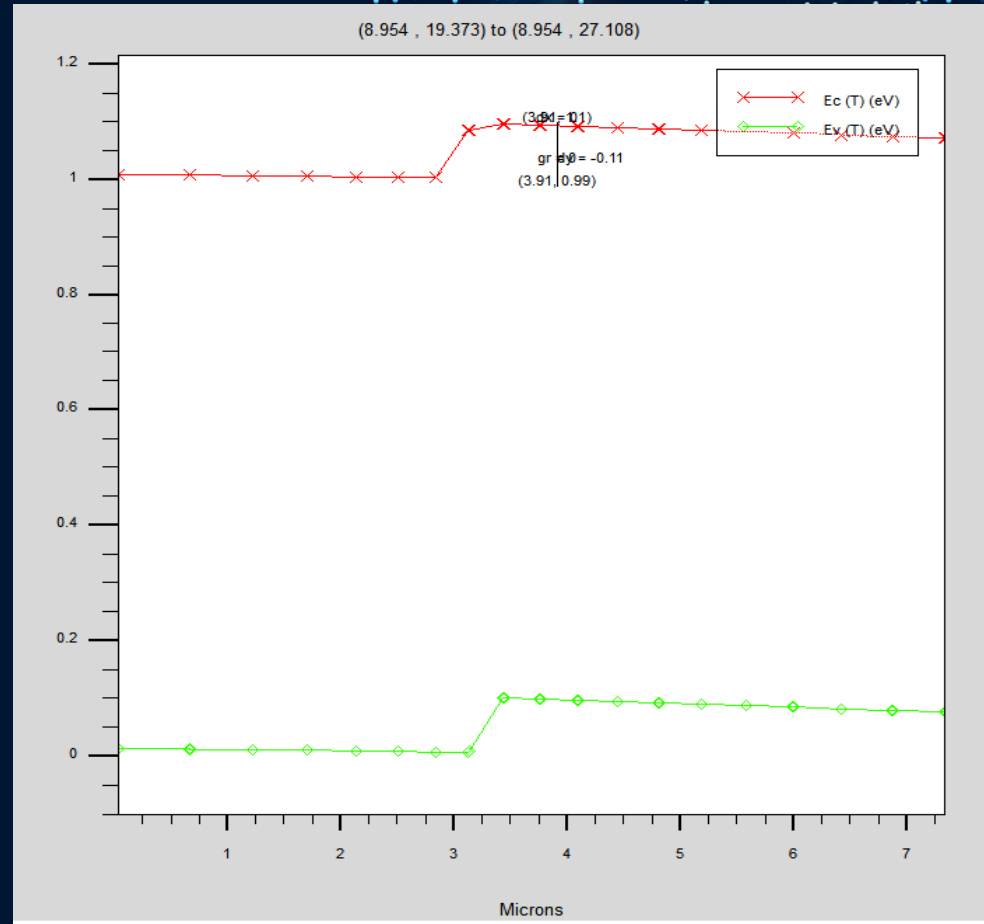
# Forward Bias: Electric Potential



# +1 V Forward Bias : Energy Band Diagrams

As we can see we have a 1 V shift  
In energy band diagrams due to the  
applied voltage.

$$\rightarrow E_{c,p} - E_{c,n} = e(V_{bi} - V_a)$$

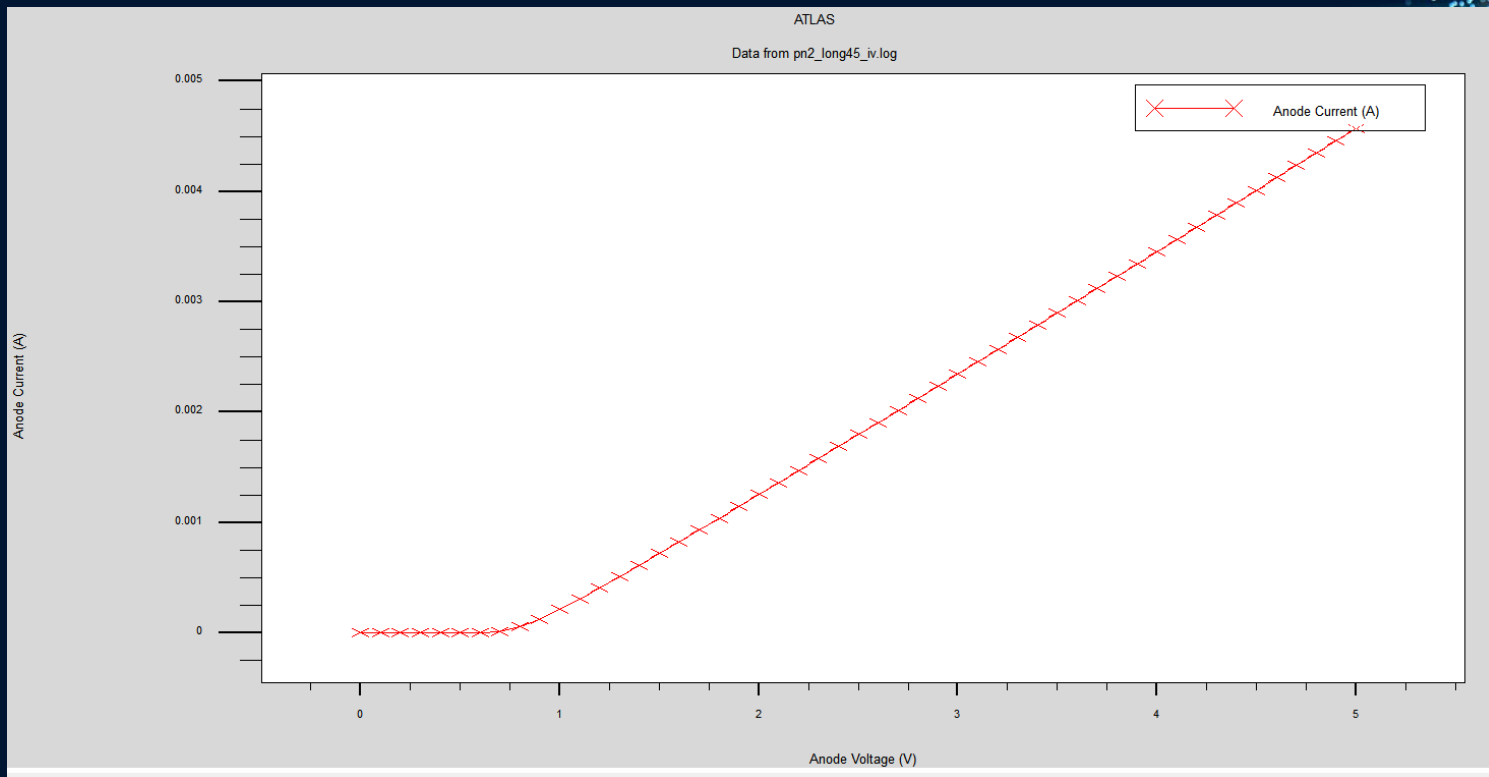


# Part 1: P-N Junction

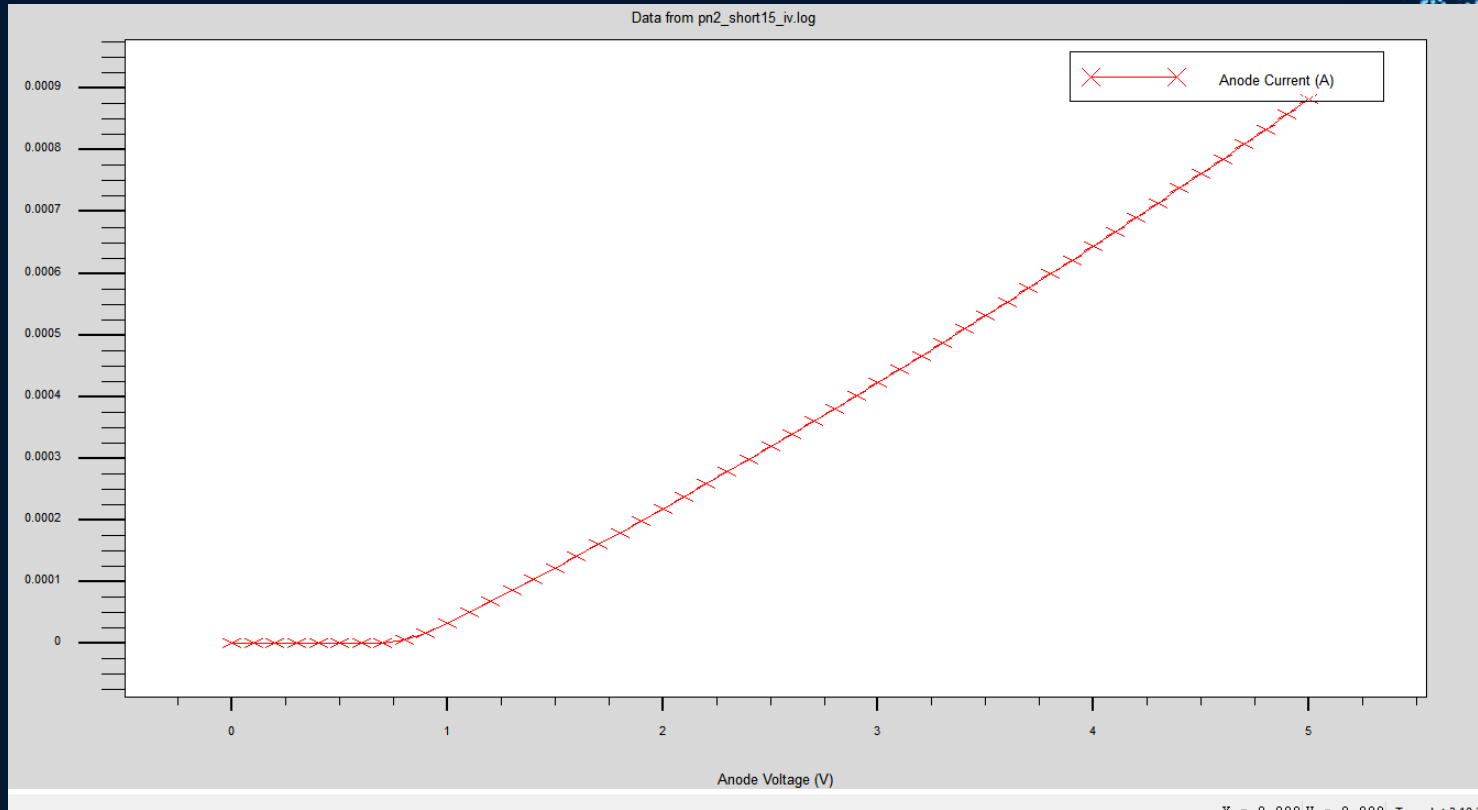
Assume that we are designing a long silicon diode with step junction and doping concentrations of  $10^{19} \text{ Atom.cm}^{-3}$  for phosphorous and  $10^{19} \text{ Atom.cm}^{-3}$  for boron

1. Draw electron and hole concentrations (mark depletion regions), electric potential (fermi level), 4 current components (drift and diffusion for both carrier types) and doping concentrations for zero bias, forward bias and reverse bias.
2. Using the information above, make a short diode and a long diode and compare their I-V characteristics.

# Long diode



# Short diode



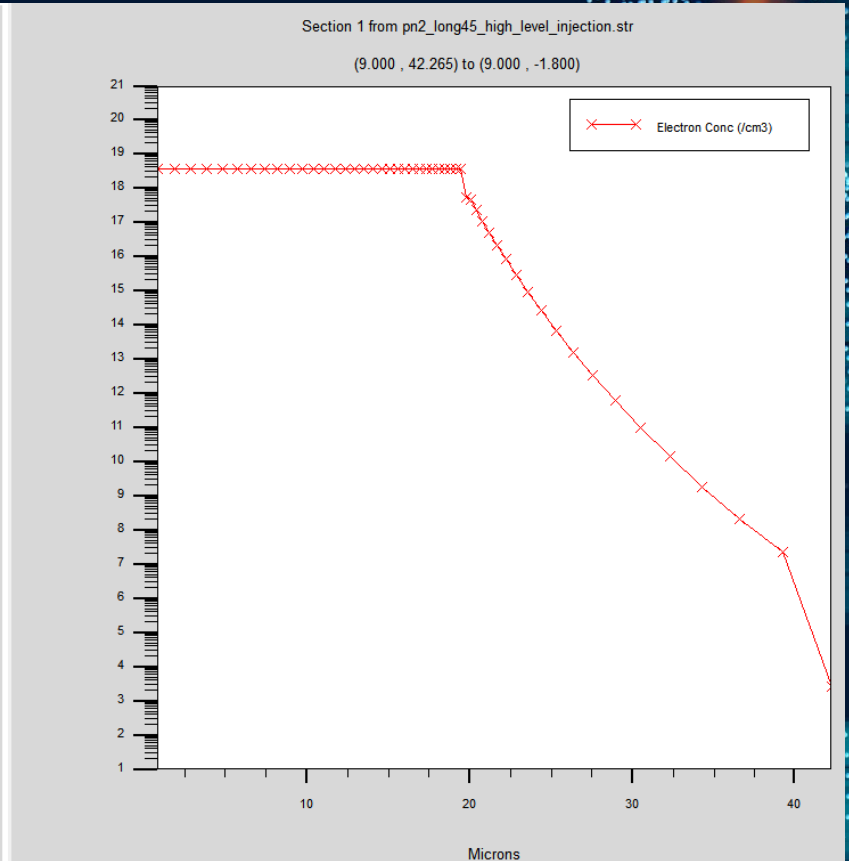
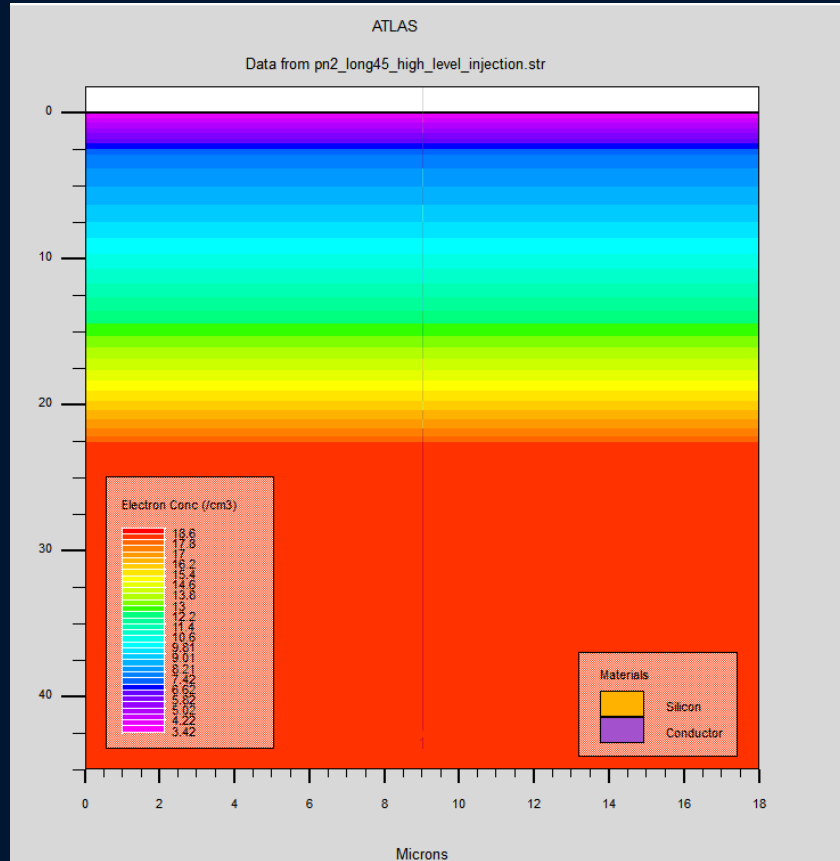


# Part 1: P-N Junction

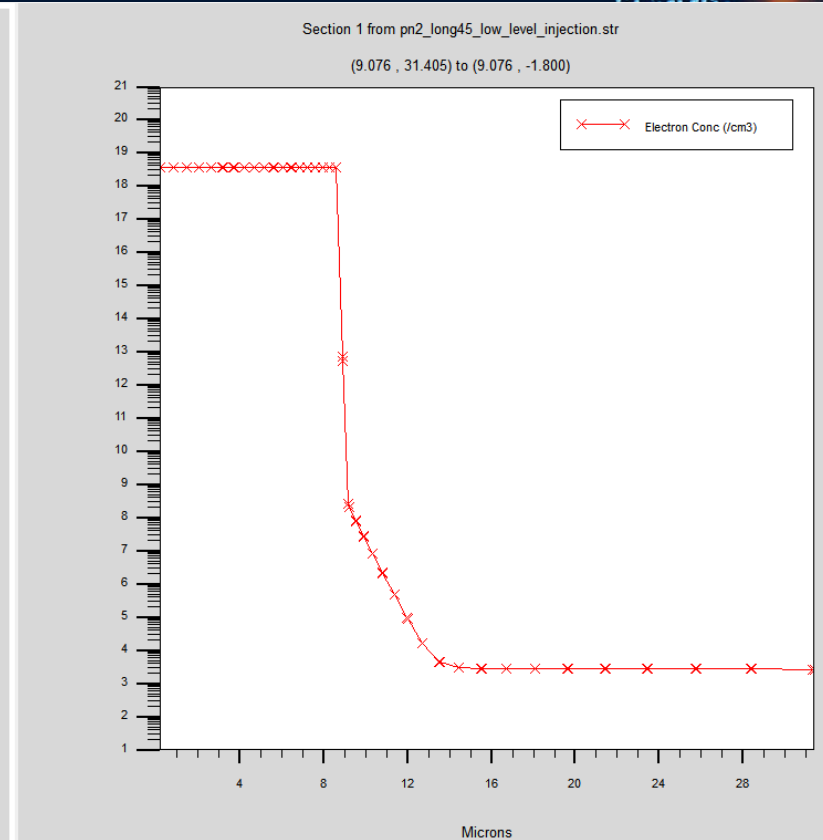
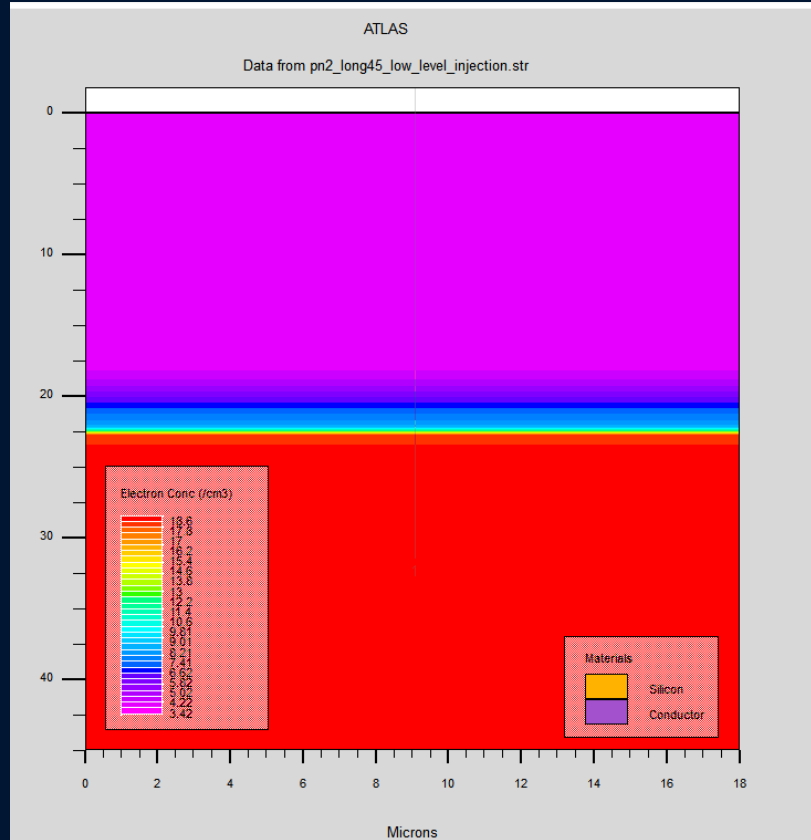
Assume that we are designing a long silicon diode with step junction and doping concentrations of  $10^{19} \text{ Atom.cm}^{-3}$  for phosphorous and  $10^{19} \text{ Atom.cm}^{-3}$  for boron

1. Draw electron and hole concentrations (mark depletion regions), electric potential (fermi level), 4 current components (drift and diffusion for both carrier types) and doping concentrations for zero bias, forward bias and reverse bias.
2. Using the information above, make a short diode and a long diode and compare their I-V characteristics.
3. For the long diode and short diode, draw the current components in low-level injection and high level injection.

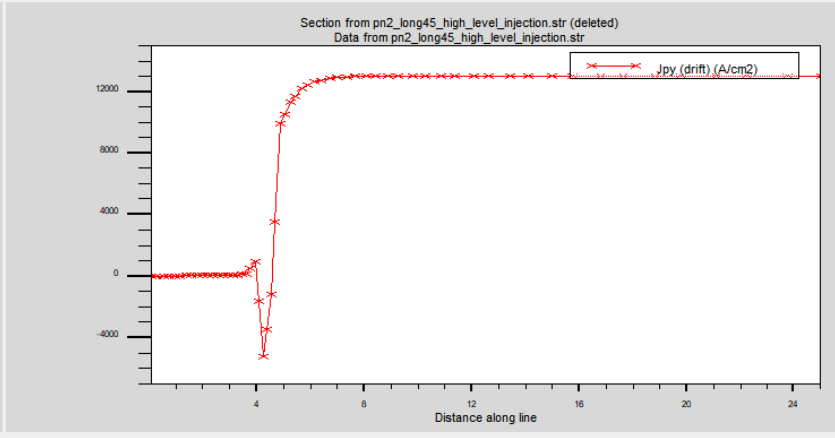
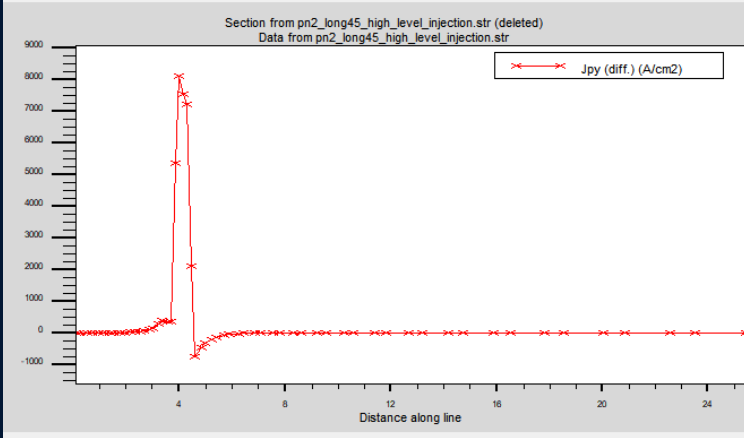
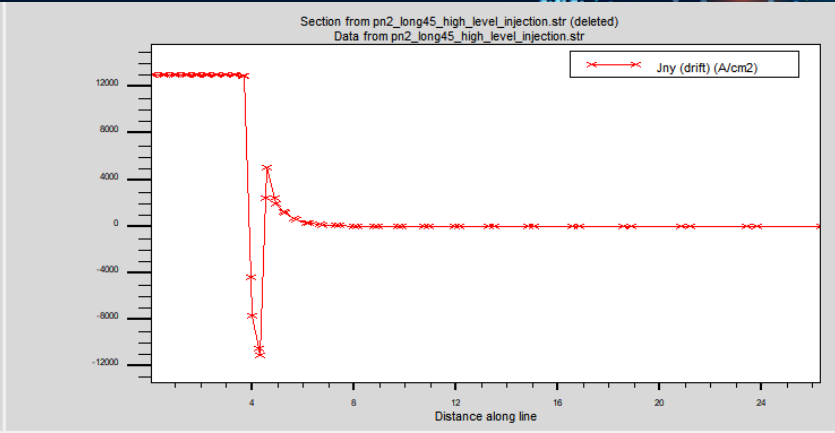
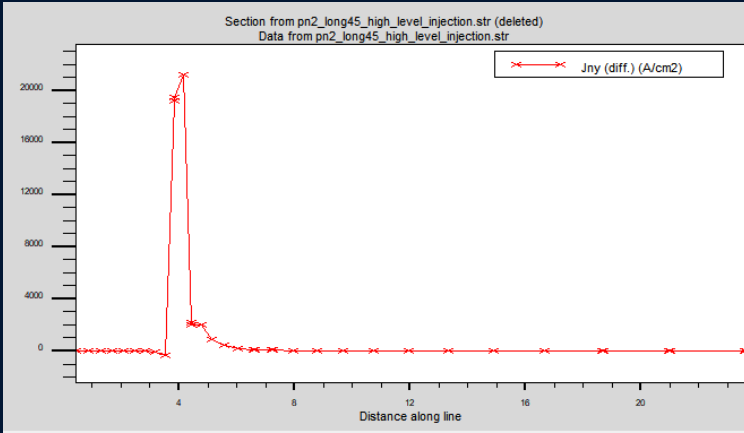
# Electron Conc. In High-Level Injection in Long Diode ( $V_{\text{forward}} = 3\text{v}$ )



# Electron Conc. In Low-Level Injection in Long Diode ( $V_{\text{forward}} = 0.3\text{v}$ )

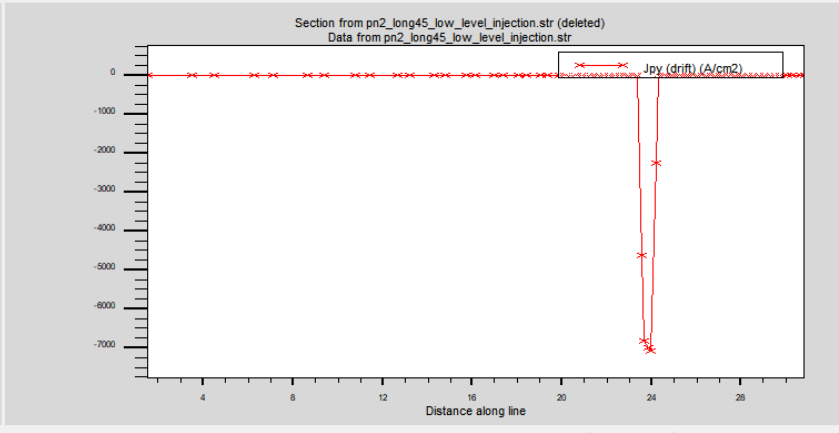
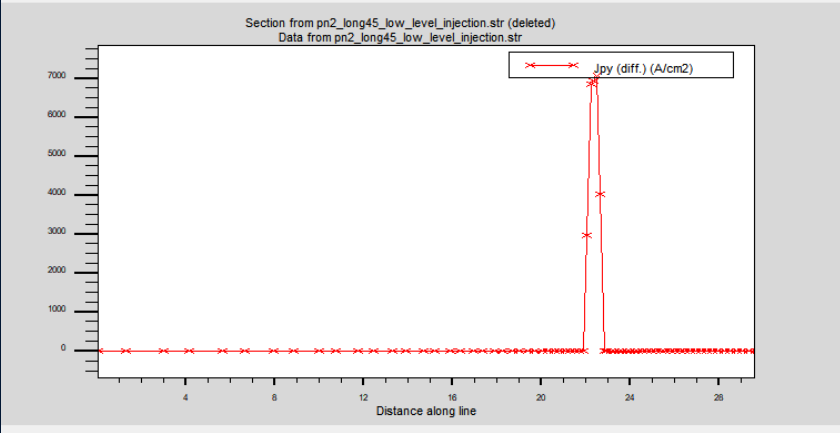
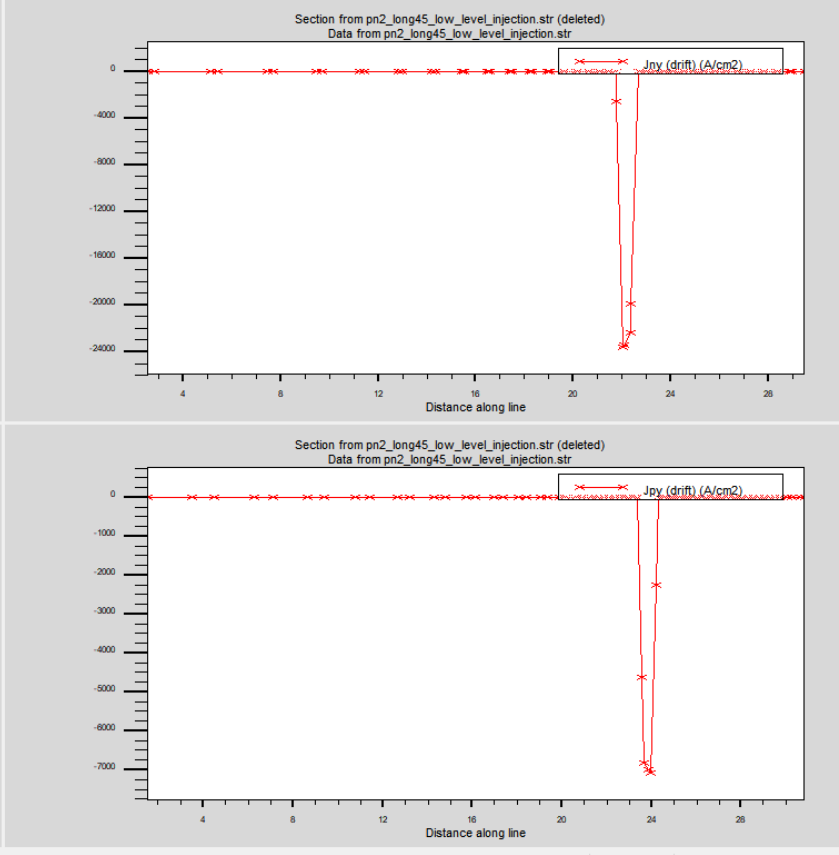
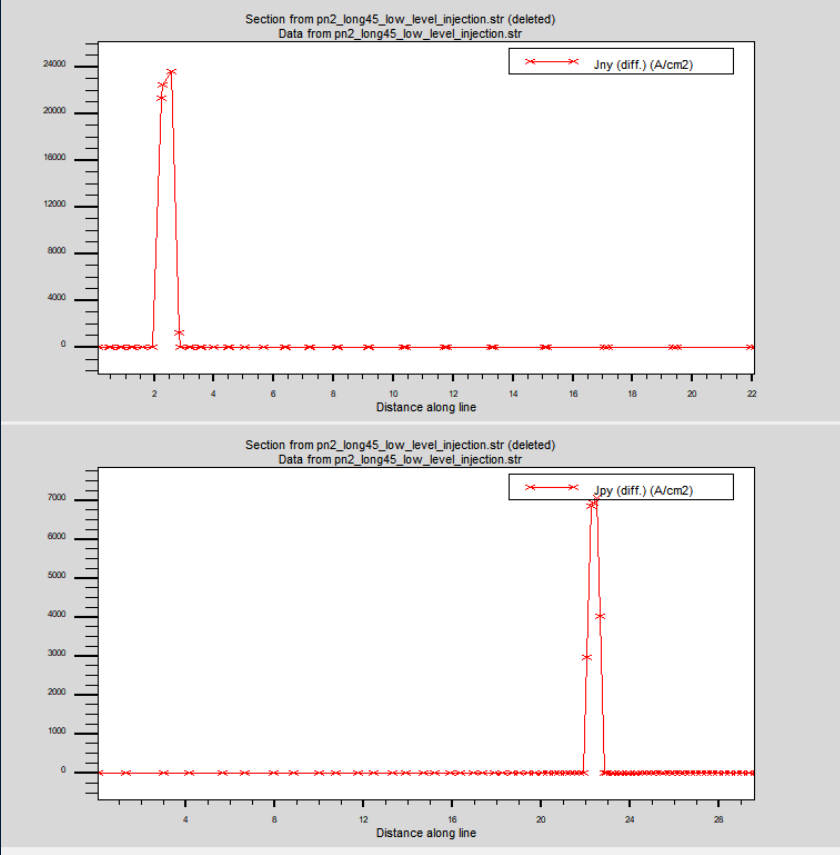


# High level injection in Long Diode : (all 4 components of current)



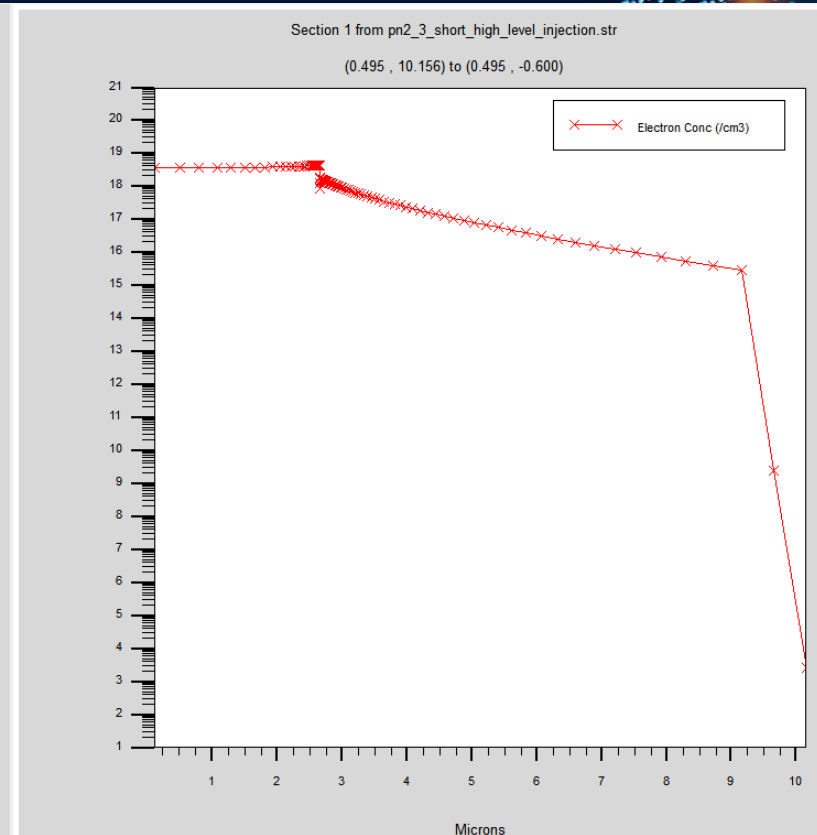
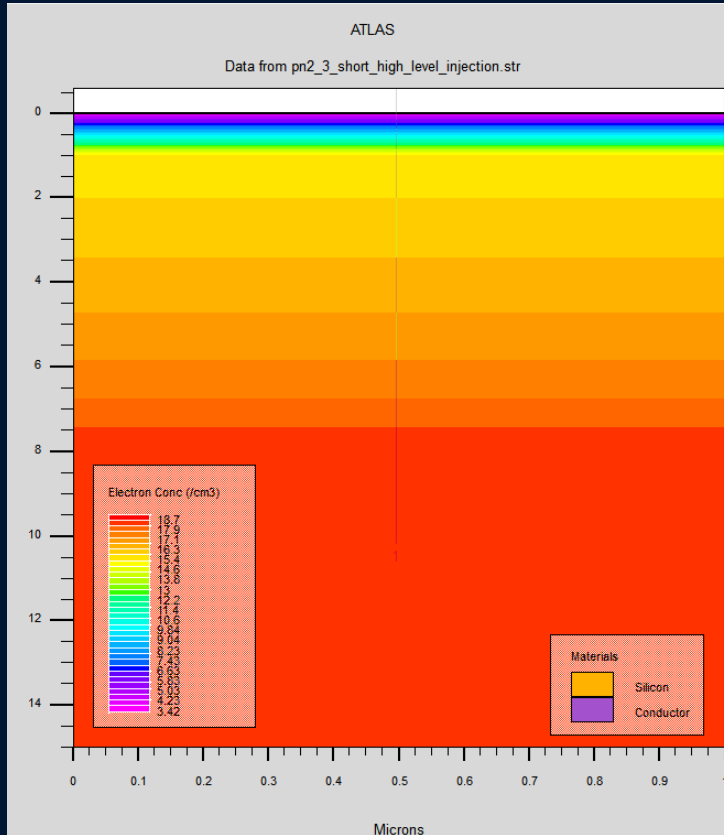
The x component of the current is negligible!

# Low level injection in Long Diode : (all 4 components of current)

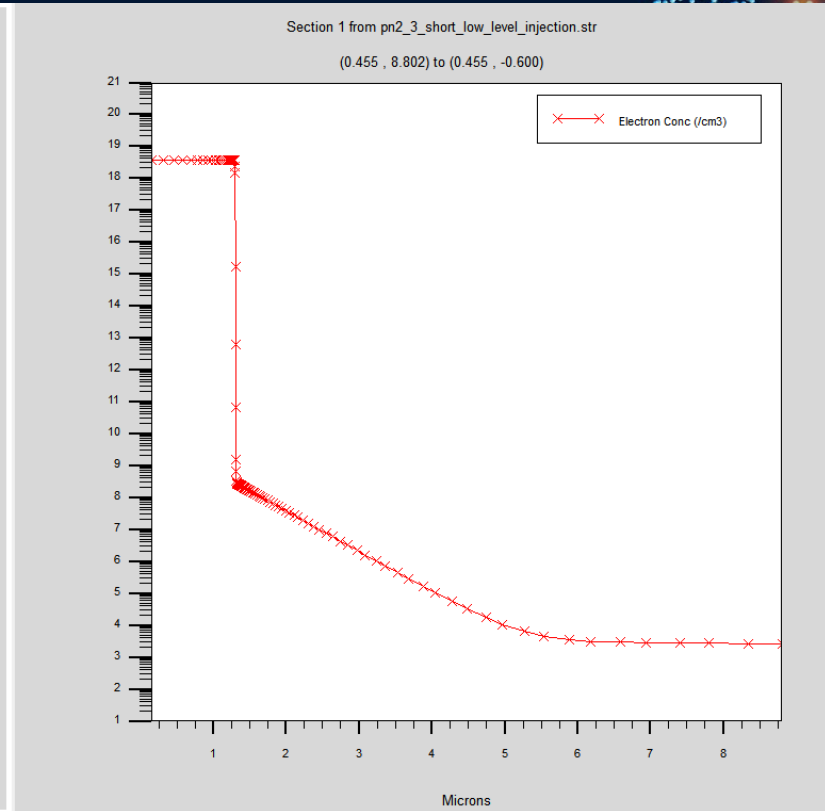
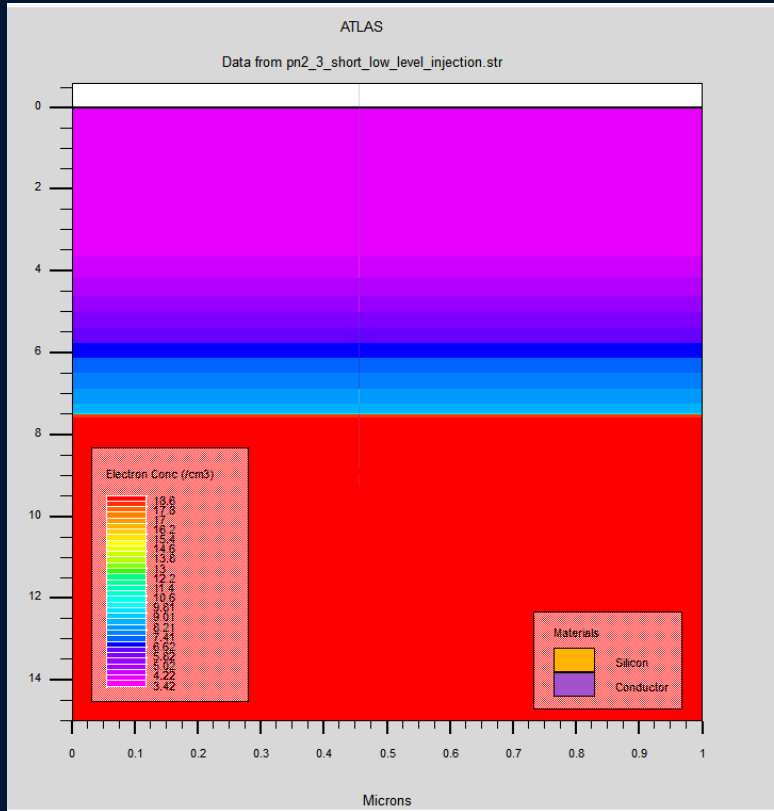


The x component of the current is negligible!

# Electron Conc. In High-Level Injection in Short Diode ( $V_{\text{forward}} = 3\text{v}$ )

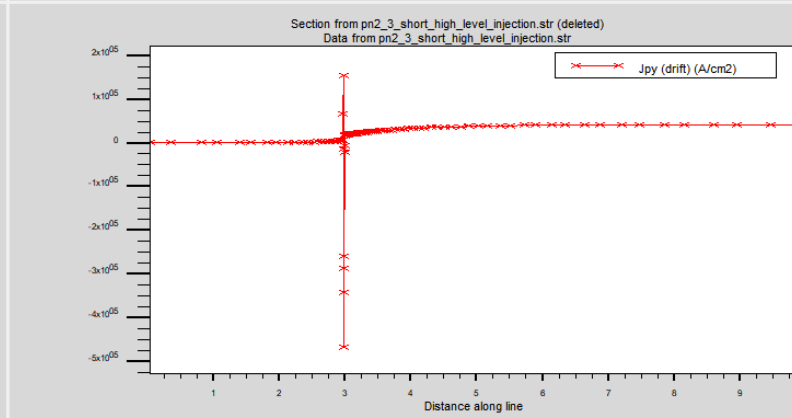
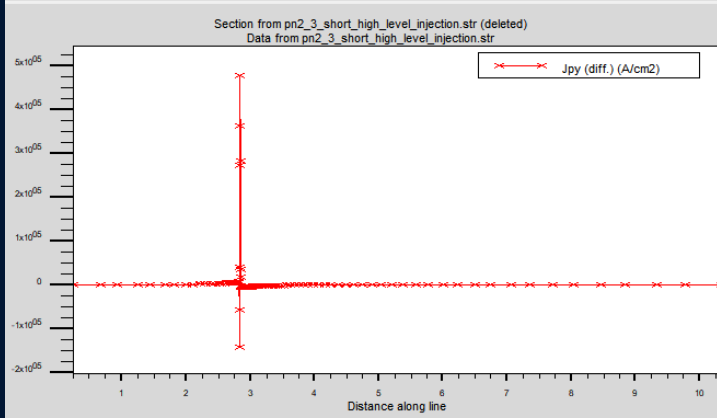
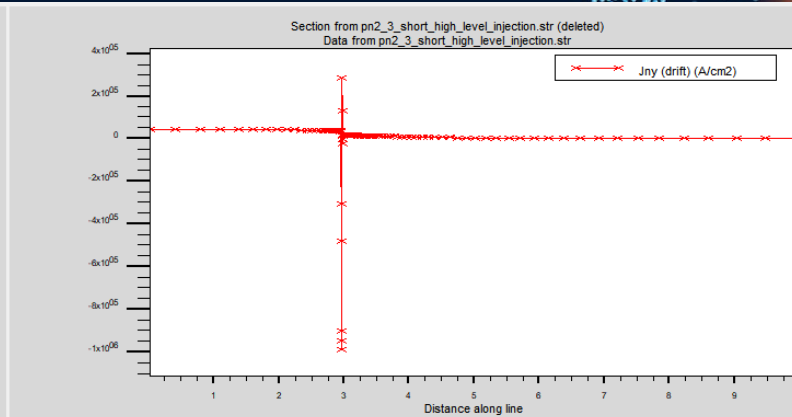
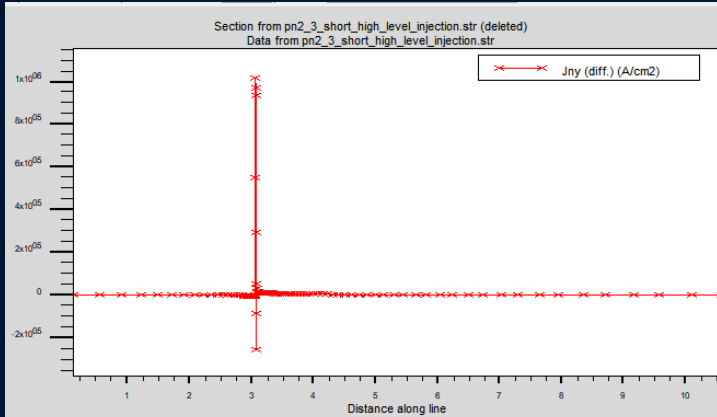


# Electron Conc. In Low-Level Injection in Short Diode ( $V_{\text{forward}} = 0.3\text{v}$ )



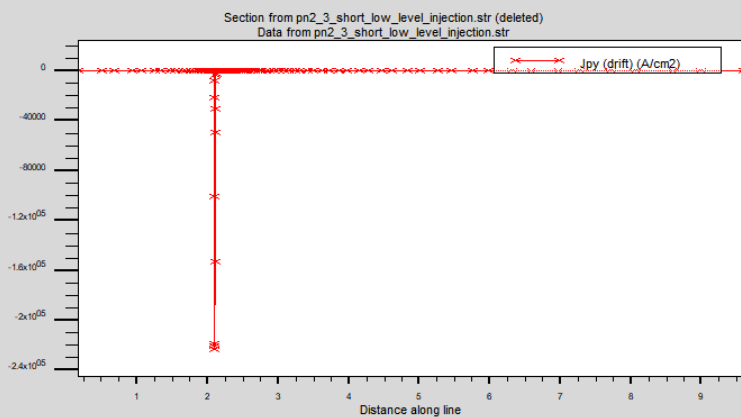
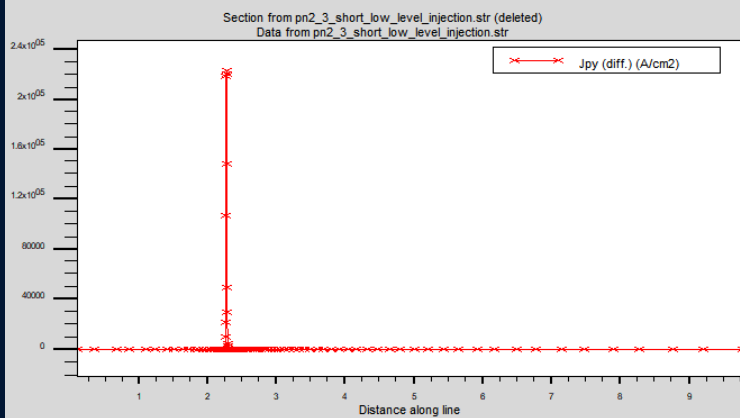
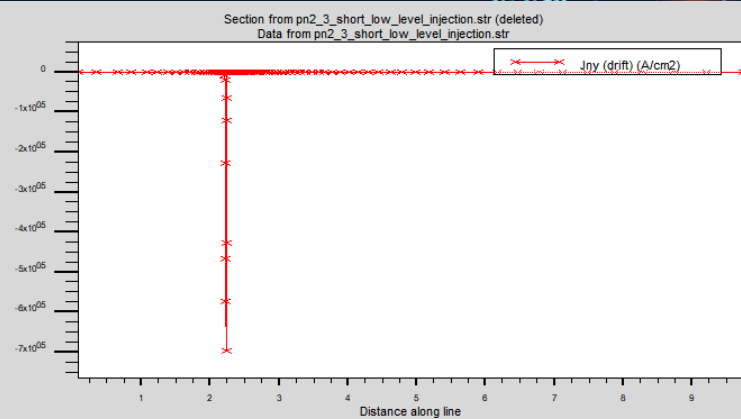
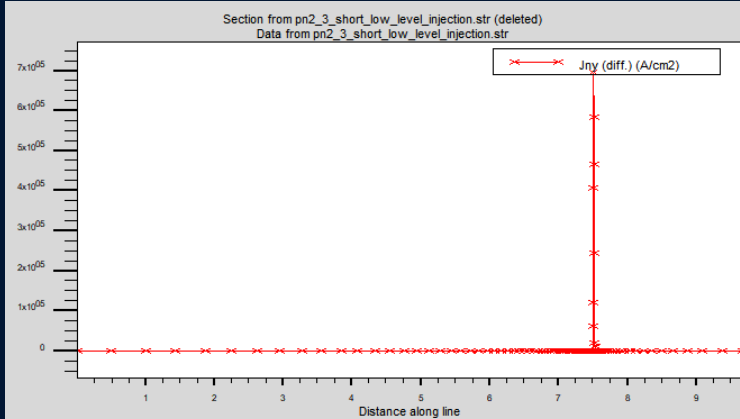


# High level injection in Short Diode : (all 4 components of current)



The x component of the current is negligible!

# Low level injection in Short Diode : (all 4 components of current)



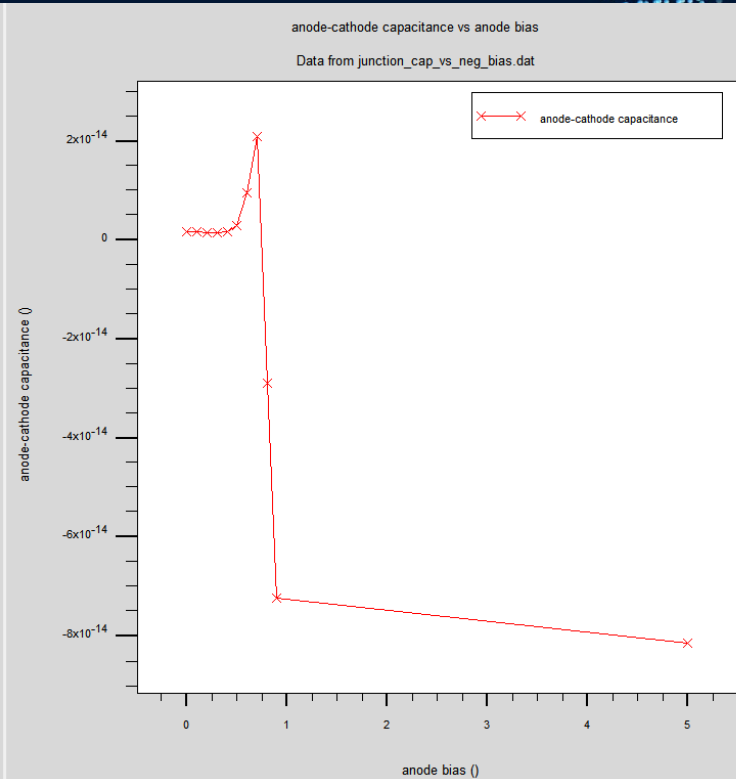
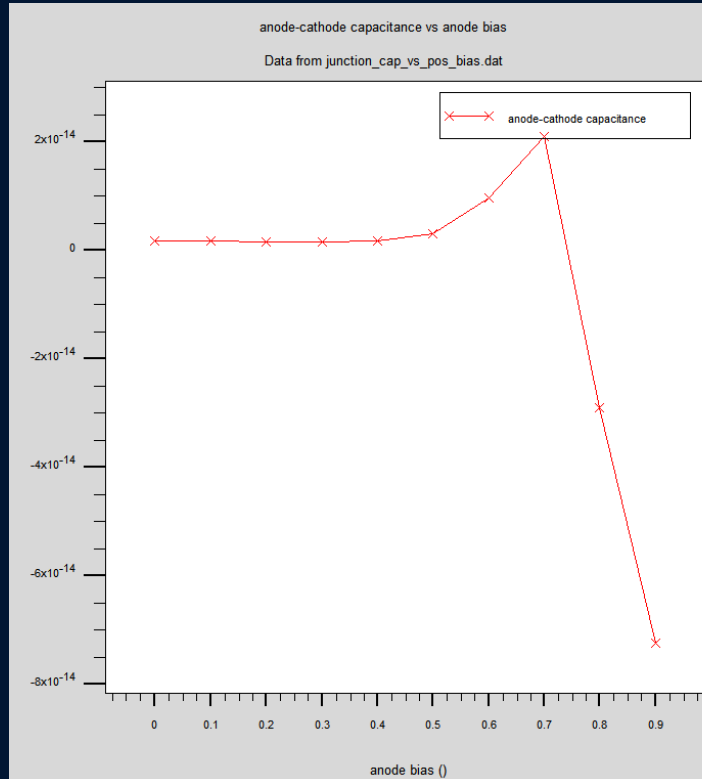
The x component of the current is negligible!

# Part 1: P-N Junction

Assume that we are designing a long silicon diode with step junction and doping concentrations of  $10^{19} \text{ Atom.cm}^{-3}$  for phosphorous and  $10^{19} \text{ Atom.cm}^{-3}$  for boron

1. Draw electron and hole concentrations (mark depletion regions), electric potential (fermi level), 4 current components (drift and diffusion for both carrier types) and doping concentrations for zero bias, forward bias and reverse bias.
2. Using the information above, make a short diode and a long diode and compare their I-V characteristics.
3. For the long diode and short diode, draw the current components in low-level injection and high level injection.
4. Extract the junction capacitance and storage capacitance for long channel diode. Sweep the bias from forward to reverse and report the change in both capacitances.

# Junction Capacitance vs Negative and Positive DC bias



## Part 1: P-N Junction

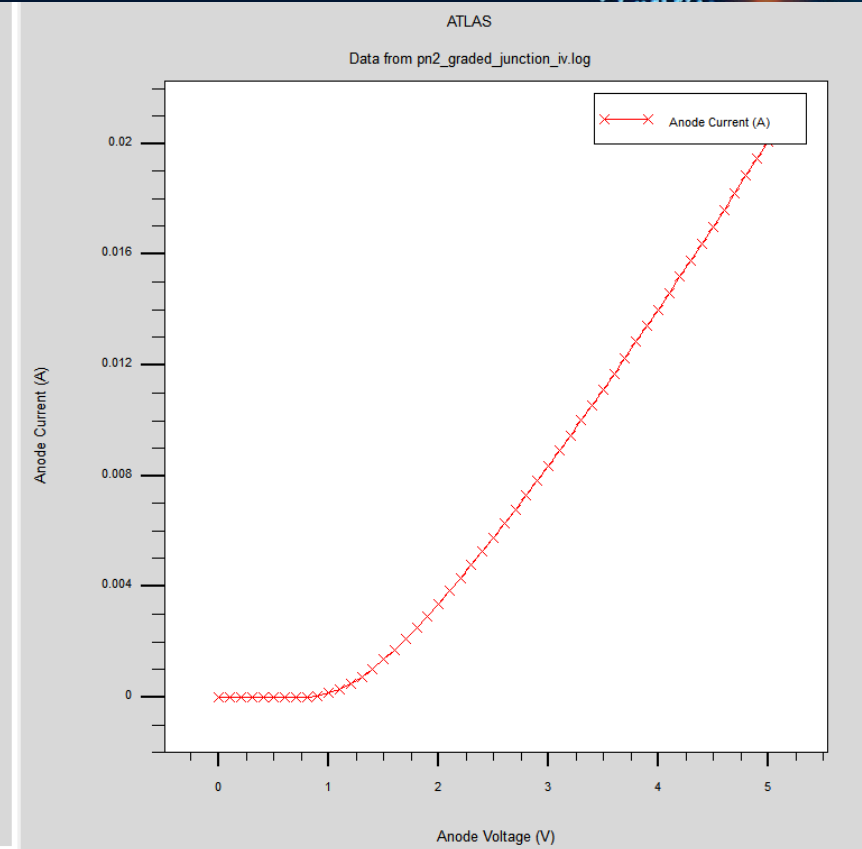
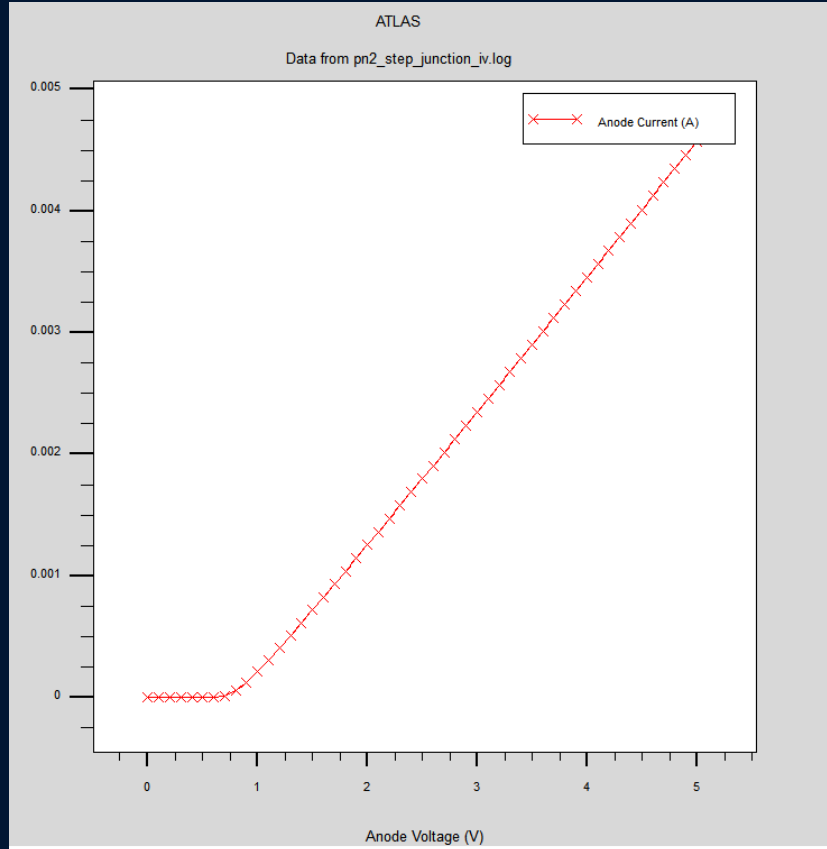
3. For the long diode and short diode, draw the current components in low-level injection and high level injection.
4. Extract the junction capacitance and storage capacitance for long channel diode. Sweep the bias from forward to reverse and report the change in both capacitances.
4. Change your junction from step to graded and compare their I-V characteristics. Then, compare doping concentrations fermi levels and junction and storage capacitance in both of them.

```
# Graded Doping Concentration
```

```
doping gaussian p.type conc=1e19 peak=0.0 junc=22.5 char=2
```

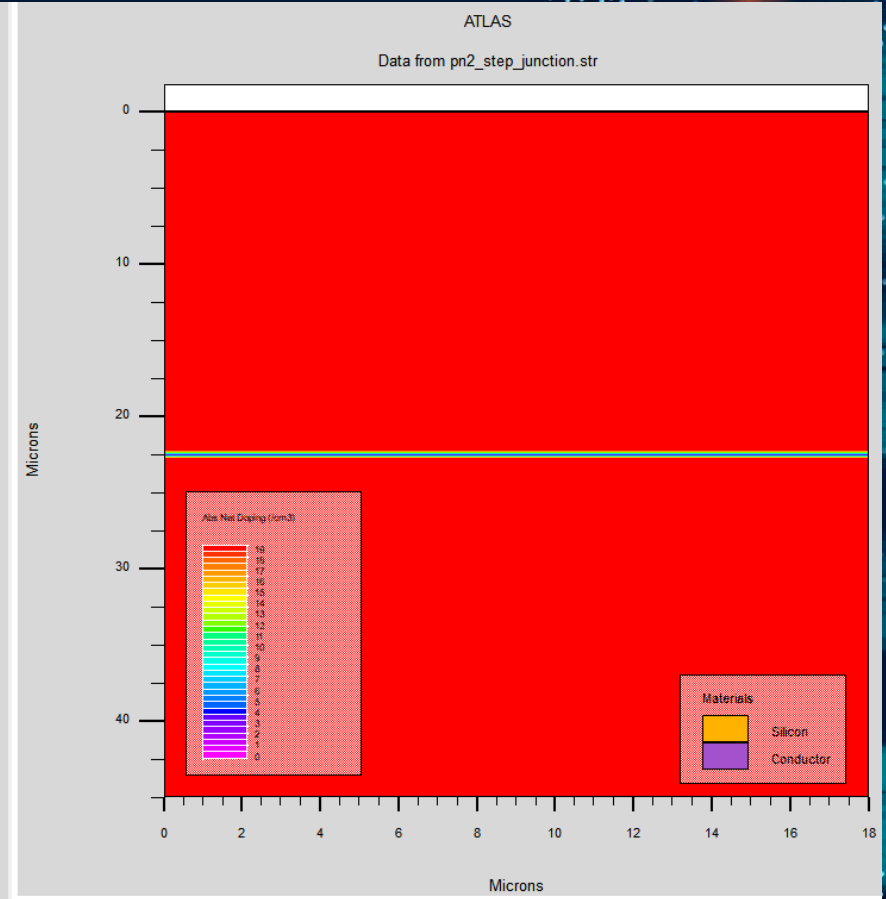
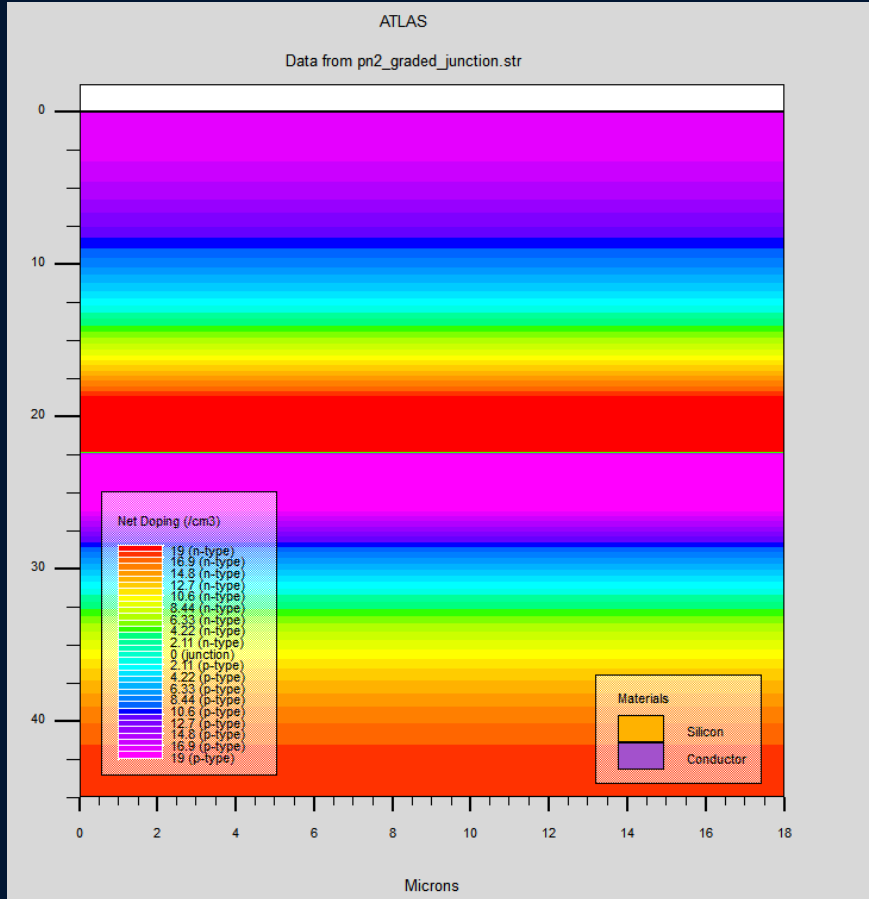
```
doping gaussian n.type conc=1e19 peak=45.0 junc=22.5 char=2
```

# I-V Characteristics comparison in Step and Graded junction

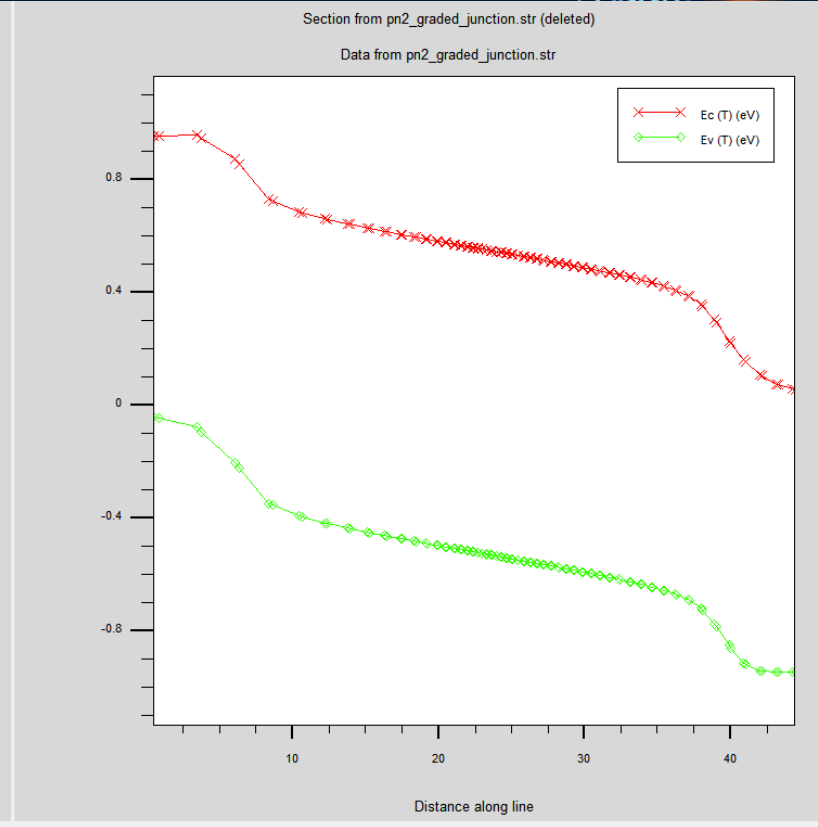
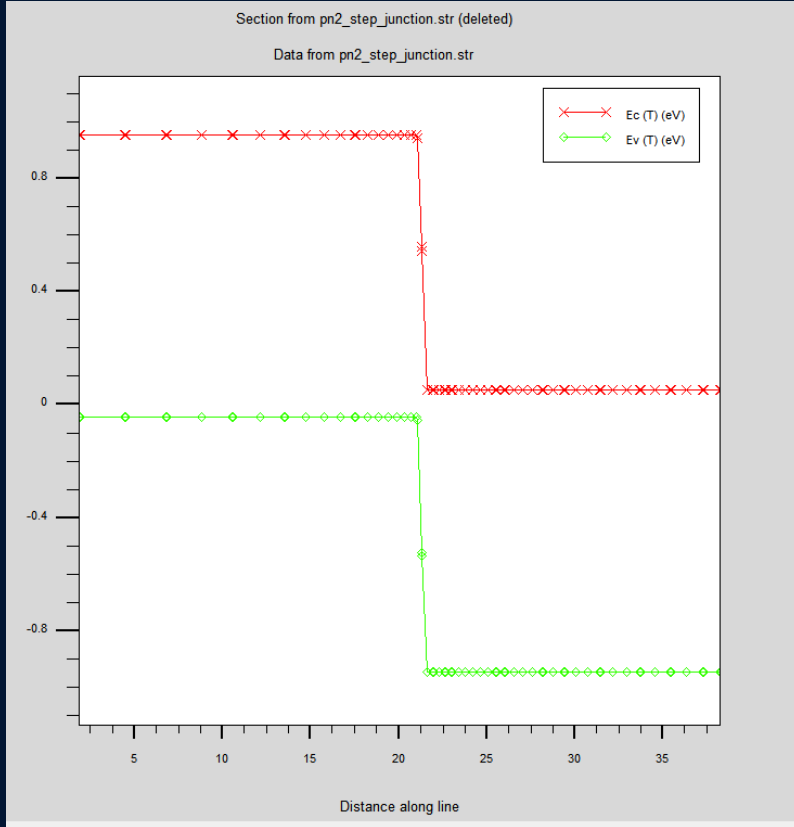




# Doping Concentrations comparison in Step and Graded junction



# Ec and Ev comparison in Step and Graded junction

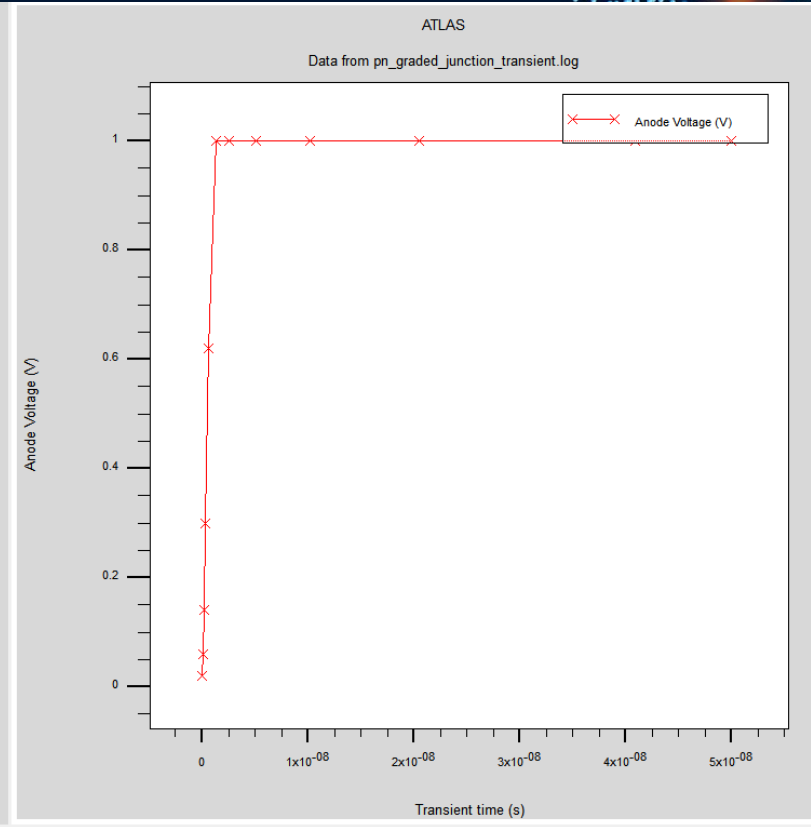
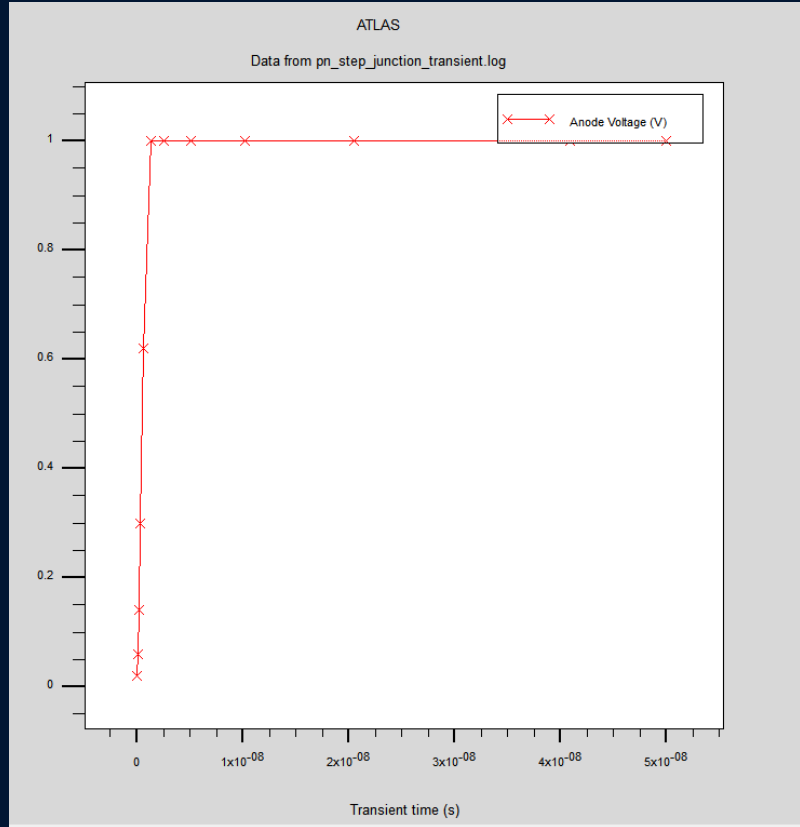


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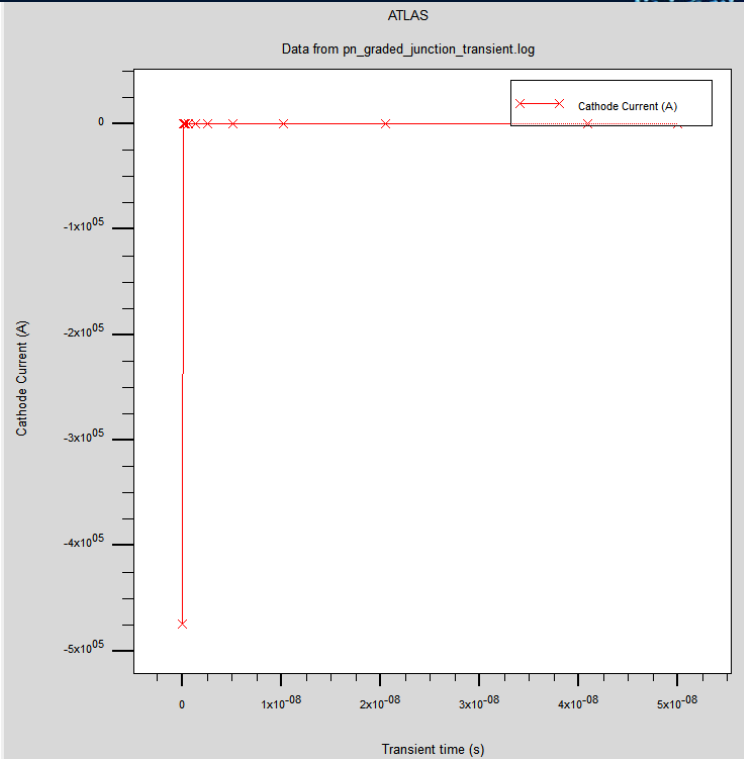
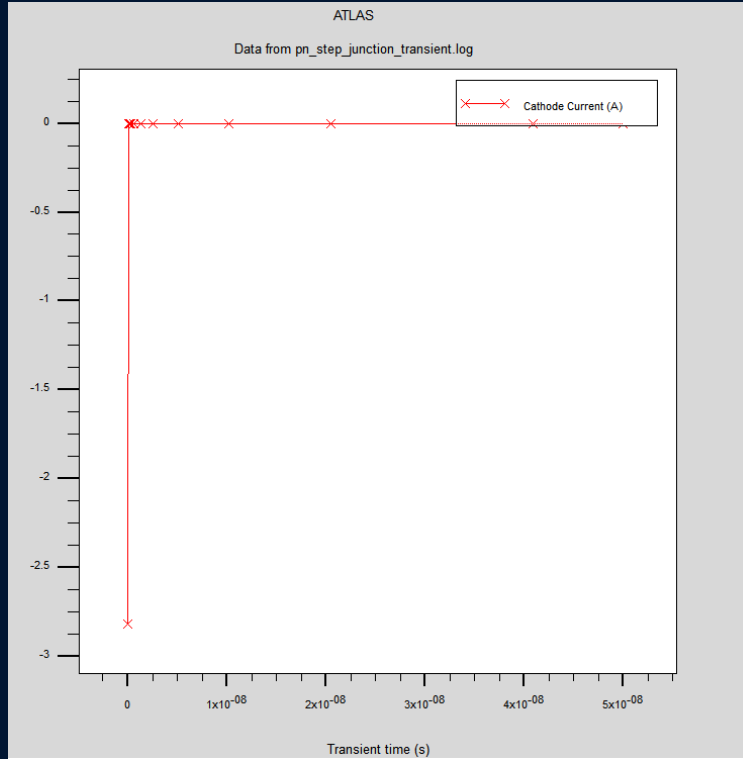
## Part 1: P-N Junction

4. Change your junction from step to graded and compare their I-V characteristics. Then, compare doping concentrations, Fermi levels, and junction and storage capacitance in both of them.
5. Simulate the transient response of long channel and short channel diodes with both graded and step junctions. Compare their switching speeds when turning on and off. (The on switching time is when the current reaches 90% of its maximum amount.)

# Transient Step input for Step and Graded junction



# Transient current output for Step and Graded junction



Unfortunately I couldn't obtain correct results for the output current though.

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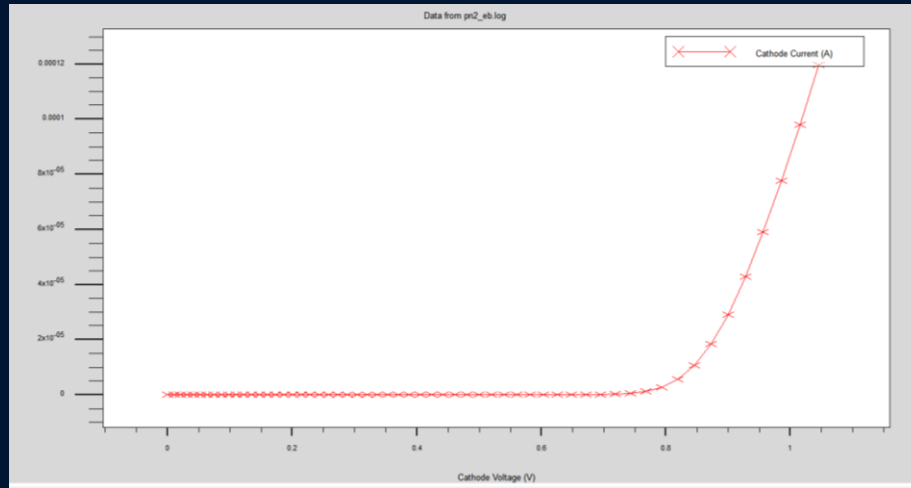
## Part 1: P-N Junction

4. Change your junction from step to graded and compare their I-V characteristics. Then, compare doping concentrations, Fermi levels, and junction and storage capacitance in both of them.
5. Simulate the transient response of long channel and short channel diodes with both graded and step junctions. Compare their switching speeds when turning on and off. (The on switching time is when the current reaches 90% of its maximum amount.)
7. Find the breakdown voltage of the step-junction diode given above using the function and simulation and compare the results.



# Curvetracing to find the breakdown voltage of the P-N

```
40  
41 curvetrace end.val=1e-4 contr.name=cathode curr.cont mincur=1e-3 nextst.ratio=1.02 step.init=0.01  
42 log outf=pn2_eb.log  
43 solve curvetrace  
44  
45 tonyplot pn2_eb.log  
46  
47 quit
```



Unfortunately my code didn't converge for other doping profiles and I couldn't fix the problem.....

# References

1. ATLAS User's Manual
2. nanoHUB.org (Introduction to Silvaco ATLAS)
3. Youtube video : <https://youtu.be/qmTRw6YTbCU> (EXPLORING PN JUNCTION DIODES with Silvaco TCAD Simulation: Compare Si, Ge, GaAs, and GaN Diodes!)
4. Youtube video: <https://youtu.be/soMdqRkgVo8> (Silvaco TCAD BREAKDOWN CURRENT SIMULATION for pn Junction Diode and MOSFET!)
5. [Atlas Device Simulation Tutorial by Maria Concetta Allia](#)
6. [Silvaco Website hints on visualizing Drift and Diffusion Current Densities](#)
7. [Silvaco document on Laser Diode Simulation](#)
8. Research Gate website forum